

10/687,689

Paul A<sub>3</sub>

L17 ANSWER 10 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN

AN 1974:444148 CAPLUS

DN 81:44148

TI Light sensitive reproduction and electron beam-sensitive material

IN Lewis, James Marvin; Wainer, Eugene

PA Horizons Inc.

SO U.S., 17 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3769023	A	19731030	US 1971-141393	19710507
	US 3820993	A	19740628	US 1973-371431	19730619
PRAI	US 1971-141393	A3	19710507		

AB A light- and electron beam-sensitive composition useful for preparing pos. or neg.

copies, planog. and deep-etched printing plates and printed circuits consists of (1) a hydroxyalkylcellulose, (2) an ethylenically unsatd. vinyl monomer, (3) a compound which produces free radicals on exposure to light or electron beams, (4) a color former which produces color by reacting with oxidizing agents or acids, (5) an organic S compound, and (6) agents for improving the shelf stability. Thus, a solution prepared from N-vinylcarbazole 150, 2,6-di-tert-butyl-p-cresol 50, triphenylstibine 10, 3-ethylrhodanine 50, CHI<sub>3</sub> 100, hydroxy-propylcellulose 400 g, CH<sub>2</sub>Cl<sub>2</sub> 4000, and THF 2000 ml was coated on a subbed polyethylene terephthalate support as a 3 mil layer, dried at 90°, exposed to UV radiation (with a total exposure of 150 mJ) through a stepwedge, and developed by heating at 170° for 90 sec to give a yellow-green image with a Dmax. of 2.22.

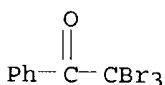
IT 7402-45-1

RL: USES (Uses)

(photoresist compns. containing vinyl compds., hydroxyalkyl cellulose and, for printed elec. circuits and printing plates)

RN 7402-45-1 CAPLUS

CN Ethanone, 2,2,2-tribromo-1-phenyl- (9CI) (CA INDEX NAME)



=&gt;

L17 ANSWER 9 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN  
 AN 1974:497798 CAPLUS  
 DN 81:97798  
 TI Light sensitive reproduction and electron beam-sensitive material  
 IN Lewis, James M.; Wainer, Eugene  
 PA Horizons Research Inc.  
 SO U.S., 18 pp. Division of U.S. 3,769,023.  
 CODEN: USXXAM

DT Patent  
 LA English

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3820993	A	19740628	US 1973-371431	19730619
	US 3769023	A	19731030	US 1971-141393	19710507
PRAI	US 1971-141393	A3	19710507		

AB Light-sensitive and electron-beam sensitive photopolymerizable compns. composed of an ethylenically unsatd. N-vinyl monomer,  $\geq 1$  organic compound capable of forming free radicals on exposure to a suitable dose of radiation, and a hydroxypropyl cellulose with a mol. weight of .apprx.25,000-1,000,000 as the binder are useful in preparing pos. and/or neg. copies, planog. and deep etch lithog. plates, thin and thick film printed circuits. Thus, a solution containing N-vinylcarbazole 150, 2,6-di-tert-butyl-p-cresol 50, Ph3Sb 10, 3-ethylrhodanine 50, CHI3 100, hydroxypropyl cellulose (mol. weight 50,000) 400 g, CH2Cl2 4000 cm3, and THF 2000 cm3 was coated on a subbed poly(ethylene terephthalate) support to a 3 mil wt thickness, dried at 90° for 30 sec, exposed through a step wedge for a total exposure of 150 mJ using 7 15-W black light fluorescent lamps, and the faint greenish yellow image fixed at 170° for 90 sec to give a Dmax. of 2.22.

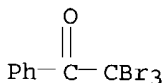
IT 7402-45-1

RL: USES (Uses)

(photoinitiator, for photopolymerizable compns. for electron-beam resist, photoresist, and photog. applications)

RN 7402-45-1 CAPLUS

CN Ethanone, 2,2,2-tribromo-1-phenyl- (9CI) (CA INDEX NAME)

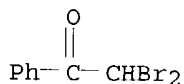


L17 ANSWER 8 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN  
 AN 1981:559910 CAPLUS  
 DN 95:159910  
 TI Plasma developable **photoresist** composition with polyvinyl formal  
 binder  
 IN Lewis, James M.; McInerney, Eugene F.  
 PA Horizons Research, Inc., USA  
 SO U.S., 5 pp.  
 CODEN: USXXAM  
 DT Patent  
 LA English  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	US 4278753	A	19810714	US 1980-124413	19800225
	JP 57196229	A2	19821202	JP 1981-79940	19810526
	JP 01049928	B4	19891026		
PRAI	US 1980-124413		19800225		

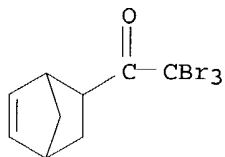
AB **Photoresist** compns. which may be completely processed by dry  
 techniques, especially by use of an O2 plasma, are composed of an N-vinyl  
**monomer** and an organic H compound in a binder which contributes  
 significantly to the utility of the composition in the fabrication of  
 microelectronic devices. Thus, a composition containing N-vinylcarbazole 3.34,  
 2,6-di-tert-butyl-p-cresol 0.33, CH3I 2.81, Butvar B-724 6.12, and a  
 PrOH-BuOH (1:1) mixture 100 g was spin coated on an oxidized Si wafer, dried  
 to give a layer of 10,000 Å thickness, imagewise exposed using a high  
 resolution test pattern, and developed using an O2 plasma for 6 min to give  
 complete resolution of the original pattern.

IT **13665-04-8**  
 RL: TEM (Technical or engineered material use); USES (Uses)  
 (**photoresist** compns. containing, oxygen plasma-developable)  
 RN 13665-04-8 CAPLUS  
 CN Ethanone, 2,2-dibromo-1-phenyl- (9CI) (CA INDEX NAME)



L17 ANSWER 6 OF 10 CAPLUS COPYRIGHT 2004 ACS on STN  
 AN 2002:353506 CAPLUS  
 DN 136:377479  
 TI High-molecular compounds for photoresists, monomeric compounds,  
**photosensitive** resin compositions, method for forming patterns  
 with the compositions, and process for production of electronic components  
 IN Shida, Naomi; Ushirogouchi, Toru; Naito, Takuya  
 PA Kabushiki Kaisha Toshiba, Japan  
 SO PCT Int. Appl., 321 pp.  
 CODEN: PIXXD2  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2002036646	A1	20020510	WO 2001-JP9567	20011031
	W: KR, US				
	JP 2002201219	A2	20020719	JP 2001-295012	20010926
	US 2003235781	A1	20031225	US 2003-425848	20030430
PRAI	JP 2000-332358	A	20001031		
	JP 2001-295012	A	20010926		
	WO 2001-JP9567	A1	20011031		
OS	MARPAT 136:377479				
AB	High-mol. compds. for photoresists, each having at least one skeleton represented by the general formula -RC(Rx1)2(ORx1), I, II, or III: -RC(Rx1)2(ORx1) I II III( R = alicyclic skeleton; Rx1= electron-attracting group, H, monovalent organic group). The compds. shows small absorption towards ≤160 nm light and provides the fine resist pattern of nanometer size and of the high etching resistance.				
IT	<b>424826-69-7</b> RL: RCT (Reactant); RACT (Reactant or reagent) ( <b>monomer</b> of high-mol. compds. for photoresists)				
RN	424826-69-7 CAPLUS				
CN	Ethanone, 1-bicyclo[2.2.1]hept-5-en-2-yl-2,2,2-tribromo- (9CI) (CA INDEX NAME)				



(FILE 'HOME' ENTERED AT 15:59:30 ON 30 DEC 2004)

FILE 'REGISTRY' ENTERED AT 15:59:39 ON 30 DEC 2004

L1 5263 SEA BUTYLSULFONYL  
D 1-3  
L2 23559 SEA ACYL  
D 1-3  
D 10-15  
L3 STRUCTURE UPLOADED  
L4 2638 SEA SSS FUL L3  
L5 STRUCTURE UPLOADED  
L6 350 SEA SSS FUL L5  
L7 STRUCTURE UPLOADED  
L8 215 SEA SSS FUL L7

FILE 'CAPLUS' ENTERED AT 16:11:41 ON 30 DEC 2004

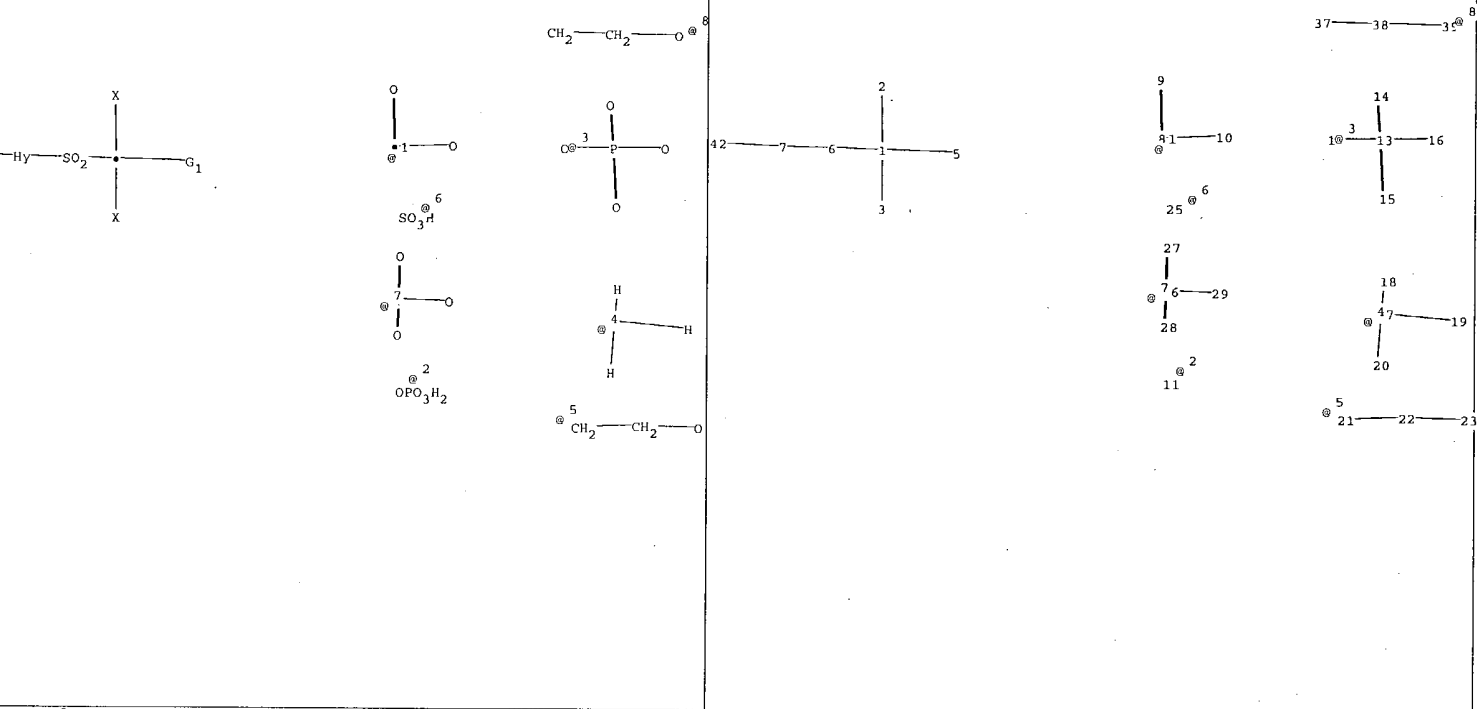
L9 85296 SEA PHOTSENSITIVE OR PHOTORESIST  
L10 3536 SEA L4  
L11 591 SEA L6  
L12 137 SEA L8  
L13 121 SEA L9 AND L10  
L14 18 SEA L9 AND L11  
L15 35 SEA L9 AND L12  
L16 169698 SEA MONOMER  
L17 10 SEA L16 AND (L13 OR L14 OR L15)  
D 1-10 BIB AB HITSTR

FILE 'REGISTRY' ENTERED AT 16:20:53 ON 30 DEC 2004

L18 188309 SEA SULFO  
D 1-4  
L19 4 SEA POLYETHYLENEOXY  
D 1-4  
L20 STRUCTURE UPLOADED  
L21 STRUCTURE UPLOADED  
L22 197 SEA SSS FUL L20  
L23 81 SEA SSS FUL L21

FILE 'CAPLUS' ENTERED AT 16:56:05 ON 30 DEC 2004

L24 107 SEA L22  
L25 84 SEA L23  
L26 6 SEA L24 AND L9  
L27 3 SEA L25 AND L9  
D L26 1-6 BIB AB HITSTR  
L28 0 SEA 16 AND (L26 OR L27)



n nodes :  
 1 2 3 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 25 26 27  
 28 29 37 38 39 42  
 n bonds :  
 1-2 1-3 1-5 1-6 6-7 7-42 8-9 8-10 12-13 13-14 13-15 13-16 17-18 17-19 17-20  
 21-22 22-23 26-27 26-28 26-29 37-38 38-39  
 t/norm bonds :  
 1-5 6-7 7-42 8-9 8-10 12-13 13-14 13-15 13-16 26-27 26-28 26-29  
 t bonds :  
 1-2 1-3 1-6 17-18 17-19 17-20 21-22 22-23 37-38 38-39

,COOH,CN,NO2,X

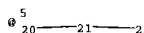
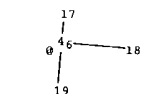
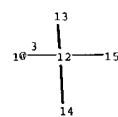
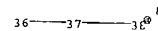
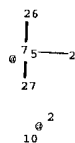
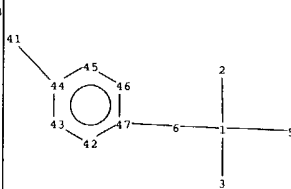
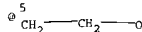
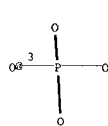
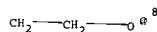
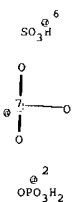
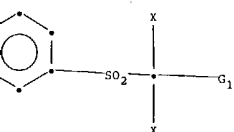
H,[\*1],[\*2],[\*3],[\*4],[\*5],[\*6],[\*7],[\*8]

ectivity :

10:1 E exact RC ring/chain 16:1 E exact RC ring/chain 29:1 E exact RC ring/chain

h level :

1:CLASS 2:CLASS 3:CLASS 5:CLASS 6:CLASS 7:Atom 8:CLASS 9:CLASS 10:CLASS 11:CLASS  
 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS  
 21:CLASS 22:CLASS 23:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS 29:CLASS 37:CLASS  
 38:CLASS 39:CLASS 42:CLASS



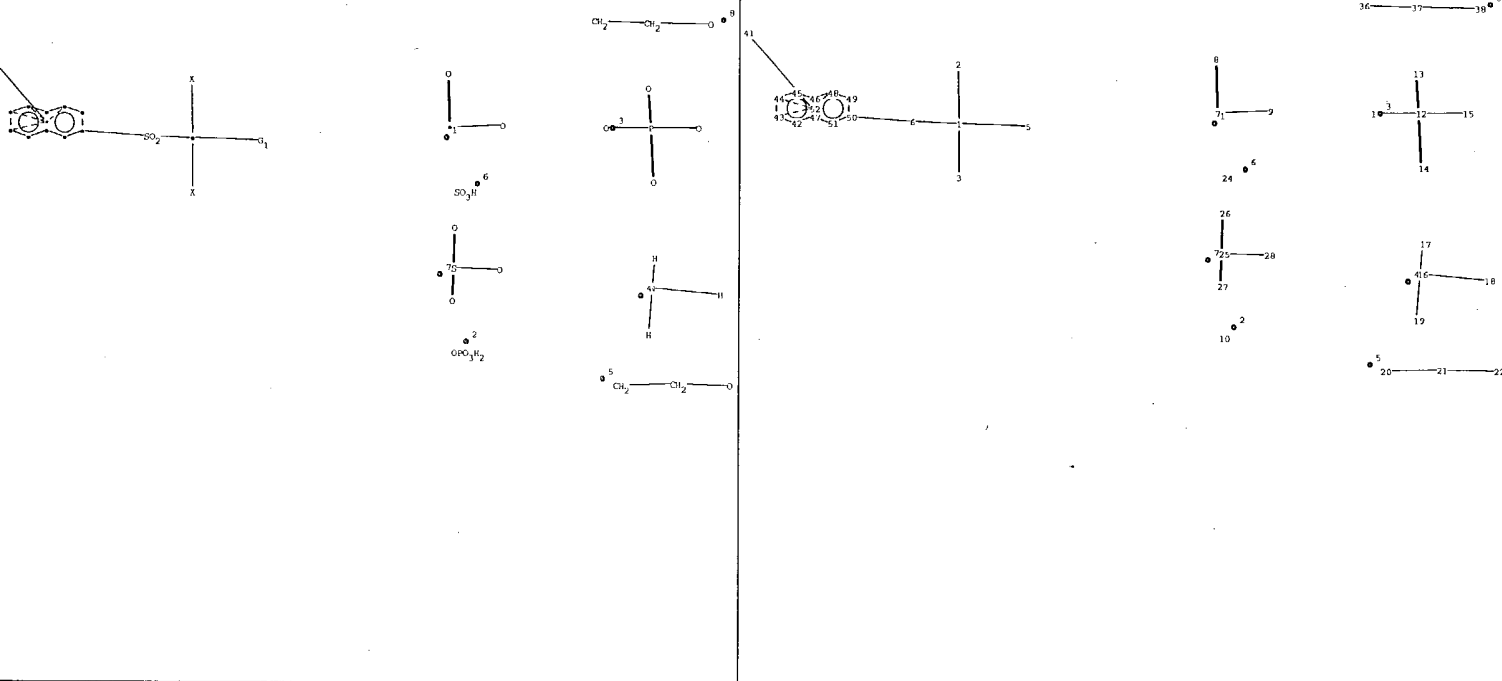
n nodes :  
 1 2 3 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 24 25 26 27  
 28 36 37 38 41  
 nodes :  
 42 43 44 45 46 47  
 n bonds :  
 1-2 1-3 1-5 1-6 6-47 7-8 7-9 11-12 12-13 12-14 12-15 16-17 16-18 16-19 20-21  
 21-22 25-26 25-27 25-28 36-37 37-38 41-44  
 bonds :  
 42-43 42-47 43-44 44-45 45-46 46-47  
 c/norm bonds :  
 1-5 7-8 7-9 11-12 12-13 12-14 12-15 25-26 25-27 25-28 41-44  
 c bonds :  
 1-2 1-3 1-6 6-47 16-17 16-18 16-19 20-21 21-22 36-37 37-38  
 alized bonds :  
 42-43 42-47 43-44 44-45 45-46 46-47

COOH,CN,NO2,X

H,[\*1],[\*2],[\*3],[\*4],[\*5],[\*6],[\*7],[\*8]

ectivity :  
 9:1 E exact RC ring/chain 15:1 E exact RC ring/chain 28:1 E exact RC ring/chain  
 n level :

1:CLASS 2:CLASS 3:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS 11:CLASS  
 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS 20:CLASS  
 21:CLASS 22:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS 36:CLASS 37:CLASS  
 8:CLASS 41:CLASS 42:CLASS 43:Atom 44:Atom 45:Atom 46:Atom 47:Atom



main nodes :  
 1 2 3 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 24 25 26 27  
 28 36 37 38 41  
 ring nodes :  
 42 43 44 45 46 47 48 49 50 51  
 main bonds :  
 1-2 1-3 1-5 1-6 6-50 7-8 7-9 11-12 12-13 12-14 12-15 16-17 16-18 16-19 20-21  
 21-22 25-26 25-27 25-28 36-37 37-38  
 ring bonds :  
 42-43 42-47 43-44 44-45 45-46 46-47 46-48 47-51 48-49 49-50 50-51  
 act/norm bonds :  
 1-5 7-8 7-9 11-12 12-13 12-14 12-15 25-26 25-27 25-28  
 act bonds :  
 1-2 1-3 1-6 6-50 16-17 16-18 16-19 20-21 21-22 36-37 37-38  
 formalized bonds :  
 42-43 42-47 43-44 44-45 45-46 46-47 46-48 47-51 48-49 49-50 50-51

:H,COOH,CN,NO2,X

:OH,[\*1],[\*2],[\*3],[\*4],[\*5],[\*6],[\*7],[\*8]

connectivity :

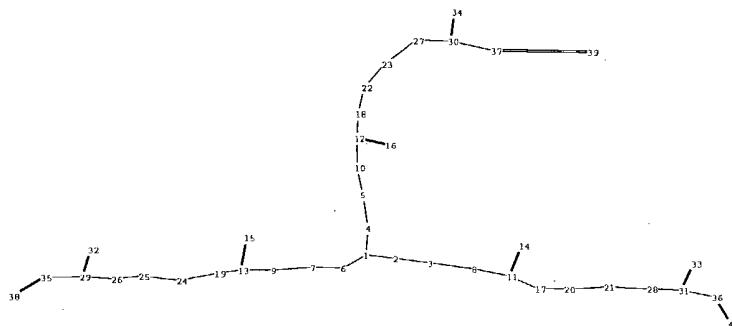
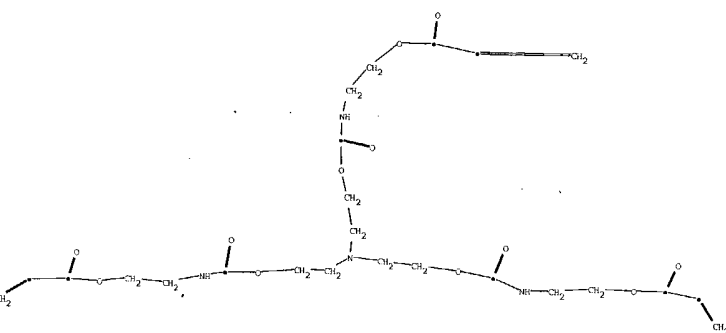
9:1 E exact RC ring/chain 15:1 E exact RC ring/chain 28:1 E exact RC ring/chain

atch level :

1:Atom 2:Atom 3:Atom 5:Atom 6:Atom 7:Atom 8:Atom 9:Atom 10:Atom 11:Atom 12:Atom  
 13:Atom 14:Atom 15:Atom 16:Atom 17:Atom 18:Atom 19:Atom 20:Atom 21:Atom 22:Atom  
 24:Atom 25:Atom 26:Atom 27:Atom 28:Atom 36:Atom 37:Atom 38:Atom 41:Atom 42:Atom  
 43:Atom 44:Atom 45:Atom 46:Atom 47:Atom 48:Atom 49:Atom 50:Atom 51:Atom 52:Atom



Monomer



main nodes :

1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 24 25  
26 27 28 29 30 31 32 33 34 35 36 37 38 39 40

main bonds :

1-2 1-4 1-6 2-3 3-8 4-5 5-10 6-7 7-9 8-11 9-13 10-12 11-14 11-17 12-16 12-18  
13-15 13-19 17-20 18-22 19-24 20-21 21-28 22-23 23-27 24-25 25-26 26-29 27-30  
28-31 29-32 29-35 30-34 30-37 31-33 31-36 35-38 36-40 37-39

fact/norm bonds :

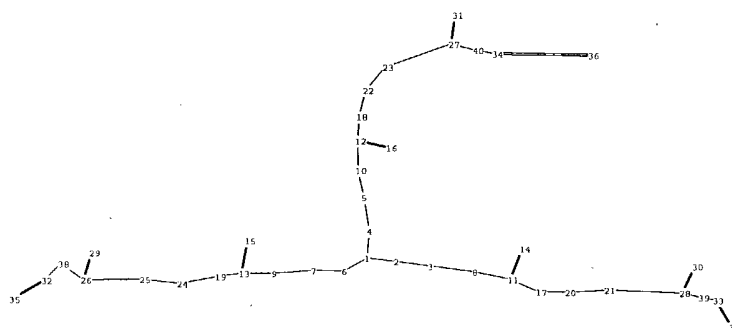
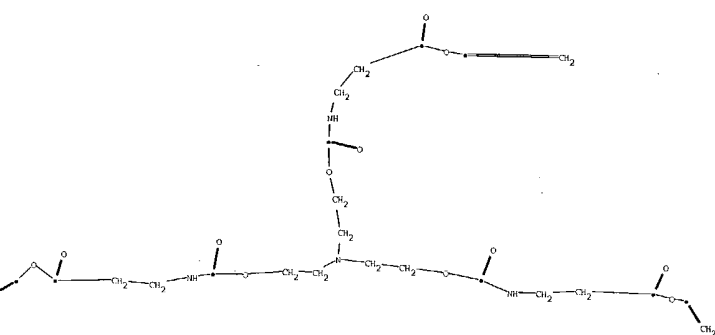
8-11 9-13 10-12 11-14 11-17 12-16 12-18 13-15 13-19 26-29 27-30 28-31 29-32  
30-34 31-33

fact bonds :

1-2 1-4 1-6 2-3 3-8 4-5 5-10 6-7 7-9 17-20 18-22 19-24 20-21 21-28 22-23  
23-27 24-25 25-26 29-35 30-37 31-36 35-38 36-40 37-39

atch level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS  
20:CLASS 21:CLASS 22:CLASS 23:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS  
29:CLASS 30:CLASS 31:CLASS 32:CLASS 33:CLASS 34:CLASS 35:CLASS 36:CLASS 37:CLASS  
38:CLASS 39:CLASS 40:CLASS



main nodes :

1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23 24 25  
26 27 28 29 30 31 32 33 34 35 36 37 38 39 40

main bonds :

1-2 1-4 1-6 2-3 3-8 4-5 5-10 6-7 7-9 8-11 9-13 10-12 11-14 11-17 12-16 12-18  
13-15 13-19 17-20 18-22 19-24 20-21 21-28 22-23 23-27 24-25 25-26 26-29 26-38  
27-31 27-40 28-30 28-39 32-35 32-38 33-37 33-39 34-36 34-40

act/norm bonds :

8-11 9-13 10-12 11-14 11-17 12-16 12-18 13-15 13-19 26-29 26-38 27-31 27-40  
28-30 28-39 32-38 33-39 34-40

act bonds :

1-2 1-4 1-6 2-3 3-8 4-5 5-10 6-7 7-9 17-20 18-22 19-24 20-21 21-28 22-23  
23-27 24-25 25-26 32-35 33-37 34-36

each level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 9:CLASS 10:CLASS  
11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS 19:CLASS  
20:CLASS 21:CLASS 22:CLASS 23:CLASS 24:CLASS 25:CLASS 26:CLASS 27:CLASS 28:CLASS  
29:CLASS 30:CLASS 31:CLASS 32:CLASS 33:CLASS 34:CLASS 35:CLASS 36:CLASS 37:CLASS  
38:CLASS 39:CLASS 40:CLASS

L5 ANSWER 4 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 2004:17487 CAPLUS  
 DN 140:84655  
 TI Light sensitive planographic printing plate precursor  
 IN Hirabayashi, Kazuhiko  
 PA Konica Corporation, Japan  
 SO Eur. Pat. Appl., 70 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English

FAN.CNT 1

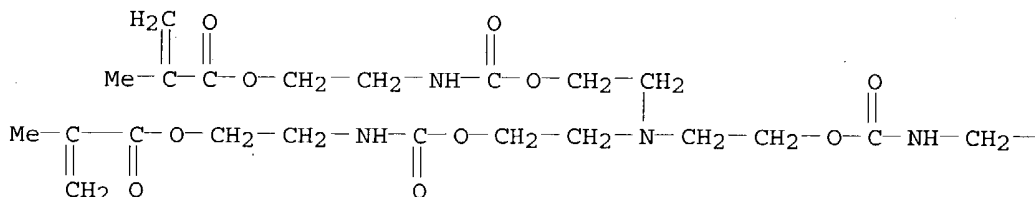
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1378793	A2	20040107	EP 2003-11834	20030526
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	US 2004005515	A1	20040108	US 2003-443943	20030522
	JP 2004086174	A2	20040318	JP 2003-171891	20030617
	JP 2004086178	A2	20040318	JP 2003-174683	20030619
	CN 1469195	A	20040121	CN 2003-149068	20030620
PRAI	JP 2002-182681	A	20020624		
	JP 2002-185985	A	20020626		
OS	MARPAT 140:84655				
AB	Disclosed are a light sensitive planog. printing plate precursor and its processing method, the precursor comprising a hydrophilic support and provided thereon, a photopolymerizable light sensitive layer containing a compound represented by the following formula R4(m-n)[(CH2C(R1)(R2)O)a-CONH(X1-NHCOO)b-X2(OO-C(R3)=CH2)c]n (Q1 = N-based group; R4 = alkyl, hydroxy alkyl; R1-2 = H, alkyl, alkoxyalkyl; R3 = H, methyl; X1 = 2-valent linkage with C2-12; X2 = 2-valent linkage, 3-valent linkage, 4-valent linkage, etc.; a = 1-4 integer; b = 0,1; c = 1-3 integer; n = integer 0-m; m = 2-4 integer) or R3(f-g)Q2[(CH2C(R5)(R6)O)d-(CH2C(CH2OCC(R7)=CH2)-HO)e-H]f (R8 = alkyl, hydroxyalkyl, aryl; R5-6 = H, alkyl, alkoxy; R7 = H, methyl; g = 2-4 integer; f = 1-g integer) and a compound represented by the following formula (R1)(R2)(R3)(R4)B-Z+ (R1-4 = alkyl, aryl, aralkyl, etc.; Z+ = cation) or I(R11-12 = alkyl with C1-12, alkynyl group with C2-12, alkoxy with C1-8, etc.; X = BF4, PF6, FeCl6, etc.; m = 1-4 integer; n = 1-5 integer).				

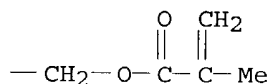
IT 124197-96-2  
 RL: TEM (Technical or engineered material use); USES (Uses)  
 (light sensitive planog. printing plate precursor)

RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediy) ester (9CI) (CA INDEX NAME)

PAGE 1-A





L5 ANSWER 5 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1994:334964 CAPLUS  
 DN 120:334964  
 TI Photopolymerizable mixture and recording material from it  
 IN Albrecht, Christine; Frass, Werner; Zertani, Rudolf  
 PA Hoechst A.-G., Germany  
 SO Ger. Offen., 10 pp.  
 CODEN: GWXXBX  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4217495	A1	19931202	DE 1992-4217495	19920527
	EP 573805	A1	19931215	EP 1993-107786	19930513
	R: DE, FR, GB, NL				
	CA 2097038	AA	19931128	CA 1993-2097038	19930526
	JP 06035189	A2	19940210	JP 1993-148443	19930527
PRAI	DE 1992-4217495	A	19920527		

OS MARPAT 120:334964

AB The title mixture comprises a polymer binder, a radical polymerizable compound, and a photoinitiator system containing: (1) a photoreducible dye, (2) a photo-dissociable trihalogenmethyl compound, and (3) a metallocene compound where the content of the binder is 5-25 weight%, the polymerizable compound is 60-90 weight%, and the photoinitiator system is 3-20 weight%. The composition

shows high photosensitivity in production of photoresist or printing plates.

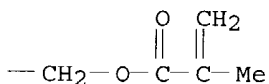
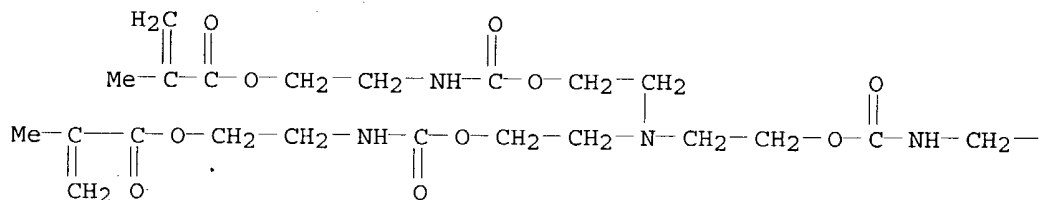
IT 124197-96-2

RL: USES (Uses)

(photopolymerizable composition containing, weight content in)

RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediy) ester (9CI) (CA INDEX NAME)



L5 ANSWER 6 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1992:140152 CAPLUS  
 DN 116:140152  
 TI Photopolymerization process for preparing printing plates and photoresists  
 IN Zertani, Rudolf; Mohr, Dieter; Matthiessen, Peter  
 PA Hoechst A.-G., Germany  
 SO Ger. Offen., 10 pp.  
 CODEN: GWXXBX  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4013358	A1	19911031	DE 1990-4013358	19900426
	EP 453953	A2	19911030	EP 1991-106188	19910418
	EP 453953	A3	19921202		
	EP 453953	B1	19970924		
	R: BE, DE, ES, FR, GB, IT, NL, SE				
	ES 2106039	T3	19971101	ES 1991-106188	19910418
	FI 9101979	A	19911027	FI 1991-1979	19910424
	CA 2041191	AA	19911027	CA 1991-2041191	19910425
	BR 9101676	A	19911210	BR 1991-1676	19910425
	JP 04261544	A2	19920917	JP 1991-122425	19910425
	JP 3118520	B2	20001218		
PRAI	DE 1990-4013358	A	19900426		

AB Photopolymn. process for preparing printing plates and photoresists. The title photopolymn. process involves irradiating a polymerizable layer containing a polymer binder, a radical polymerizable ethylenically unsatd. compound with  $\geq 1$  ethylenically unsatd. end group(s), and a radical polymerization initiator (e.g. metallocene compound). The imaging material can be irradiated with a visible light ( $>400$  nm) for hardening before, during, or after imagewise-irradiation (heat will release in short time).

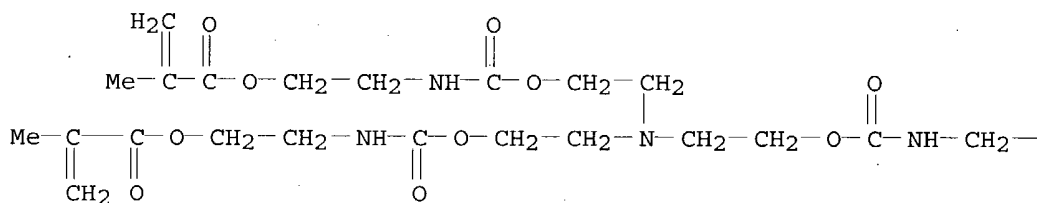
IT 124197-96-2

RL: USES (Uses)  
 (photoresist containing)

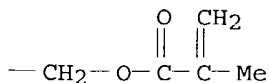
RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediyl) ester (9CI) (CA INDEX NAME)

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L5 ANSWER 7 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1992:117246 CAPLUS  
 DN 116:117246  
 TI Photopolymerizable composition and recording material produced therefrom  
 IN Zertani, Rudolf; Mohr, Dieter; Rode, Klaus  
 PA Hoechst A.-G., Germany  
 SO Eur. Pat. Appl., 13 pp.  
 CODEN: EPXXDW  
 DT Patent  
 LA German  
 FAN.CNT 1

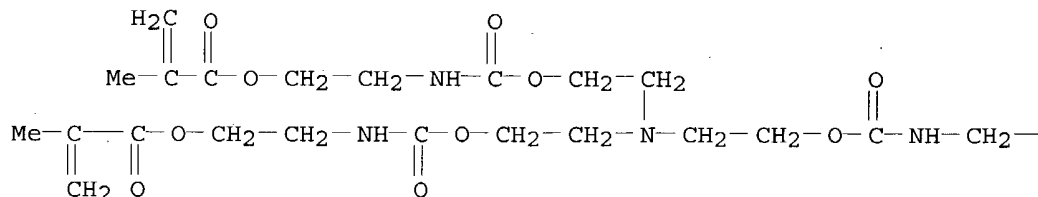
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 447930	A2	19910925	EP 1991-103783	19910313
	EP 447930	A3	19920226		
	EP 447930	B1	19970709		
	R: AT, CH, DE, DK, ES, FR, GB, IT, LI, NL				
	DE 4008815	A1	19910926	DE 1990-4008815	19900320
	AT 155259	E	19970715	AT 1991-103783	19910313
	ES 2103279	T3	19970916	ES 1991-103783	19910313
	CA 2038284	AA	19910921	CA 1991-2038284	19910314
	BR 9101072	A	19911105	BR 1991-1072	19910319
	AU 9173649	A1	19910926	AU 1991-73649	19910320
	AU 631731	B2	19921203		
	JP 04221958	A2	19920812	JP 1991-81595	19910320
PRAI	DE 1990-4008815	A	19900320		

AB The title material comprises a polymeric binder, a radical polymerizable compound with  $\geq 1$  polymerizable group and  $\geq 1$  photooxidizable group in the mol., and a photoinitiator, where the photoinitiator is a metallocene. The recording material may be a combination of a binder from methacrylic acid-n-hexyl methacrylate-styrene copolymer with acid value 190, triethylene glycol dimethacrylate monomer, and a photoinitiator from dicyclopentadienylbis(pentafluorophenyltitanium). The material has improved sensitivity and thermal stability. The material can be used for printing plates or photoresists.

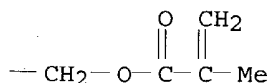
IT **124197-96-2**  
 RL: USES (Uses)  
 (photopolymerizable composition containing, in presence of metallocene photoinitiator)

RN 124197-96-2 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediylloxycarbonylimino-2,1-ethanediyl) ester (9CI) (CA INDEX NAME).

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PAGE 1-B



L5 ANSWER 8 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1990:542302 CAPLUS

DN 113:142302

TI Photopolymerizable composition and its use

IN Mueller-Hess, Waltraud; Mohr, Dieter; Frass, Werner; Rode, Klaus

PA Hoechst A.-G., Germany

SO Ger. Offen., 18 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3831782	A1	19900329	DE 1988-3831782	19880919
	EP 360151	A3	19910424	EP 1989-117005	19890914
	R: DE, FR, GB				
	JP 02151606	A2	19900611	JP 1989-241659	19890918
PRAI	DE 1988-3831782	A	19880919		

AB The title composition contains: a binder, an acrylic or alkylacrylic acid ester with a polyol, and a photoinitiator composition containing a photoreducible dye and

a photodecomposable trihalogen Me compound, and the binder has a photooxidizable group. The mixture is especially useful for photoresists or printing plate production and has improved photosensitivity.

IT 124197-96-2

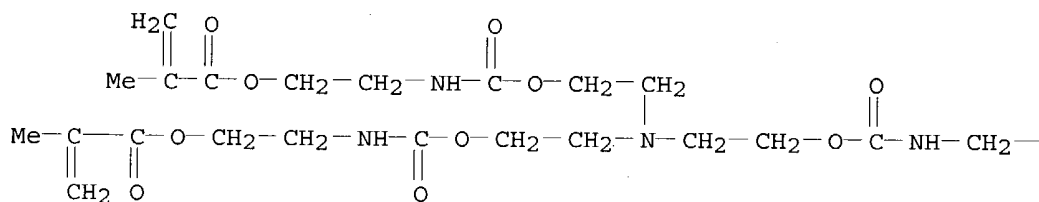
RL: USES (Uses)

(photopolymerizable composition containing)

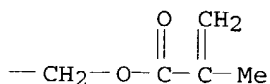
RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediyl) ester (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



L5 ANSWER 9 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1990:488280 CAPLUS

DN 113:88280

TI Photopolymerizable imaging materials with decreased sensitivity toward oxygen

IN Zertani, Rudolf; Mohr, Dieter

PA Hoechst A.-G., Germany

SO Ger. Offen., 11 pp.

CODEN: GWXXBX

DT Patent  
LA German  
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3825836	A1	19900208	DE 1988-3825836	19880729
	EP 352630	A2	19900131	EP 1989-113306	19890720
	EP 352630	A3	19900801		
	EP 352630	B1	19940817		
	R: DE, FR, GB, IT, NL				
	CA 1337677	A1	19951205	CA 1989-606446	19890724
	JP 02103051	A2	19900416	JP 1989-194419	19890728
	JP 2736124	B2	19980402		
	KR 135076	B1	19980418	KR 1989-10797	19890729
	US 5273862	A	19931228	US 1992-913753	19920717
PRAI	DE 1988-3825836	A	19880729		
	US 1989-381832	B1	19890719		

AB Photopolymerizable imaging materials, which are especially useful in preparing lithog. plates, are composed of a support, a photopolymerizable layer, and a top layer that has little permeability to O and contains a polymer that binds O and is completely soluble in water. The top layer may be prepared from poly(vinyl alc.) and a polyalkylenimine. Thus, a lithog. plate prepared from a photopolymerizable imaging material having a top layer prepared from a 7% aqueous poly(vinyl alc.) solution and Polyimine P showed excellent storage stability.

IT 124197-96-2

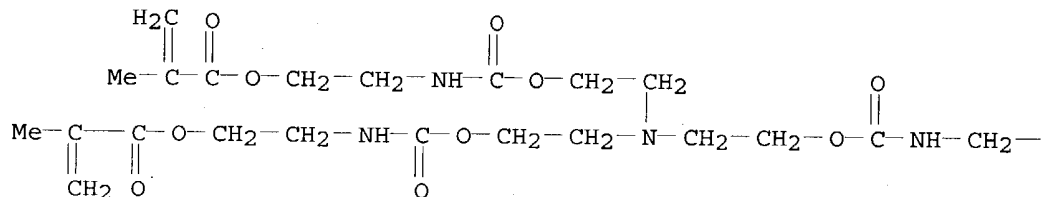
RL: USES (Uses)

(photopolymerizable imaging material containing, with polymer oxygen barrier layer for lithog. plate preparation)

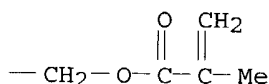
RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediyl) ester (9CI) (CA INDEX NAME)

PAGE 1-A



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L5 ANSWER 10 OF 10 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1990:14306 CAPLUS

DN 112:14306

TI Photopolymerizable mixture and recording material therefrom

IN Rode, Klaus; Mohr, Dieter; Frass, Werner; Gerstorff, Joachim

PA Hoechst A.-G., Fed. Rep. Ger.

SO Eur. Pat. Appl., 18 pp.

CODEN: EPXXDW



DT Patent  
LA German  
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 321828	A2	19890628	EP 1988-120775	19881213
	EP 321828	A3	19890906		
	EP 321828	B1	19931110		
	R: DE, FR, GB, NL				
	DE 3743457	A1	19890706	DE 1987-3743457	19871222
	FI 8805877	A	19890623	FI 1988-5877	19881220
	DK 8807118	A	19890623	DK 1988-7118	19881221
	BR 8806781	A	19890829	BR 1988-6781	19881221
	JP 02001714	A2	19900108	JP 1988-320795	19881221
	JP 2758179	B2	19980528		
	US 4987055	A	19910122	US 1988-287276	19881221
	AU 8827394	A1	19890622	AU 1988-27394	19881222
	AU 610962	B2	19910530		
	ZA 8809581	A	19890927	ZA 1988-9581	19881222
PRAI	DE 1987-3743457	A	19871222		

AB Photopolymerizable mixts. for the preparation of photoresists and printing plates are composed of a polymer binder, an acrylic acid or alkacrylic acid ester of a polyhydric alc. having a group photooxidizable by a photoreducible dye, a photoreducible benzoxanthene or benzothioxanthene dye as a photoinitiator, a radiation-cleavable trihalomethyl compound, and, optionally, an acridine or phenazine compound as a photoinitiator. The mixts. have increased sensitivity. Thus, a roughened and hydrophilized Al printing plate was overcoated with a composition containing a Me methacrylate-methacrylic acid copolymer (acid number 110 and average mol. wt 35,000), N[CH<sub>2</sub>CHMeCOCH<sub>2</sub>CH(CH<sub>2</sub>O<sub>2</sub>CCMe:CH<sub>2</sub>)OH]<sub>3</sub>, the dye I, 2,4-bis(trichloromethyl)-6-(4-styrylphenyl)-s-triazine, and propylene glycol mono-Me ether, dried, imagewise exposed through an edge filter, and developed to show 4 steps.

IT 124197-96-2

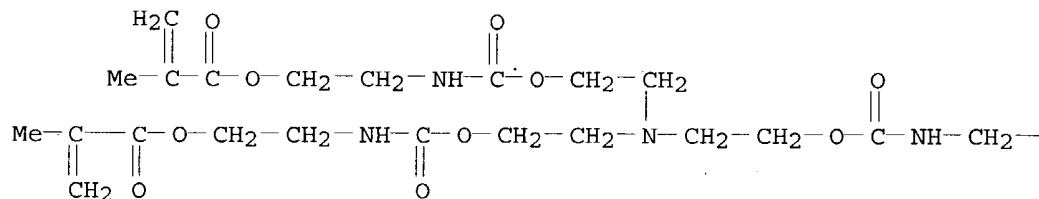
RL: USES (Uses)

(photopolymerizable compns. containing benzoxanthene or benzothioxanthene derivative photoinitiator and, for photoresists and printing plate fabrication)

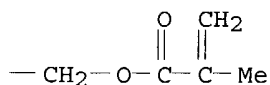
RN 124197-96-2 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris(2,1-ethanediyloxycarbonylimino-2,1-ethanediy) ester (9CI) (CA INDEX NAME)

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L8 ANSWER 6 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 2004:17487 CAPLUS  
 DN 140:84655  
 TI Light sensitive planographic printing plate precursor  
 IN Hirabayashi, Kazuhiko  
 PA Konica Corporation, Japan  
 SO Eur. Pat. Appl., 70 pp.  
 CODEN: EPXXDW

DT Patent  
 LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1378793	A2	20040107	EP 2003-11834	20030526
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	US 2004005515	A1	20040108	US 2003-443943	20030522
	JP 2004086174	A2	20040318	JP 2003-171891	20030617
	JP 2004086178	A2	20040318	JP 2003-174683	20030619
	CN 1469195	A	20040121	CN 2003-149068	20030620
PRAI	JP 2002-182681	A	20020624		
	JP 2002-185985	A	20020626		

OS MARPAT 140:84655

AB Disclosed are a light sensitive planog. printing plate precursor and its processing method, the precursor comprising a hydrophilic support and provided thereon, a photopolymerizable light sensitive layer containing a compound represented by the following formula  $R_4(m-n)[(CH_2C(R_1)(R_2)O)a-CONH(X_1-NHCOO)b-X_2(OO-C(R_3)=CH_2)c]_n$  ( $Q_1 = N$ -based group;  $R_4 =$  alkyl, hydroxy alkyl;  $R_1-2 = H$ , alkyl, alkoxyalkyl;  $R_3 = H$ , methyl;  $X_1 = 2$ -valent linkage with  $C_2-12$ ;  $X_2 = 2$ -valent linkage, 3-valent linkage, 4-valent linkage, etc.;  $a = 1-4$  integer;  $b = 0, 1$ ;  $c = 1-3$  integer;  $n =$  integer  $0-m$ ;  $m = 2-4$  integer) or  $R_3(f-g)Q_2[(CH_2C(R_5)(R_6)O)d-(CH_2C(CH_2OOC(R_7)=CH_2)-HO)e-H]_f$  ( $R_8 =$  alkyl, hydroxyalkyl, aryl;  $R_5-6 = H$ , alkyl, alkoxy;  $R_7 = H$ , methyl;  $g = 2-4$  integer;  $f = 1-g$  integer) and a compound represented by the following formula  $(R_1)(R_2)(R_3)(R_4)B-Z^+$  ( $R_1-4 =$  alkyl, aryl, aralkyl, etc.;  $Z^+ =$  cation) or  $I(R_{11-12} =$  alkyl with  $C_1-12$ , alkynyl group with  $C_2-12$ , alkoxy with  $C_1-8$ , etc.;  $X = BF_4, PF_6, FeCl_6$ , etc.;  $m = 1-4$  integer;  $n = 1-5$  integer).

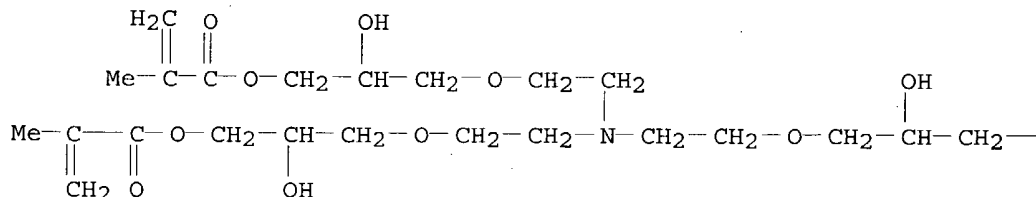
IT 123735-16-0

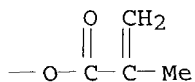
RL: TEM (Technical or engineered material use); USES (Uses)  
 (light sensitive planog. printing plate precursor)

RN 123735-16-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

PAGE 1-A





LB ANSWER 7 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1999:378455 CAPLUS

DN 131:46119

TI Quaternary ammonium salts, their preparation, and photocurable antifogging compositions

IN Lee, Hyun-Woo; Park, Yong-Hoon; Kim, Sang-Keun; Shin, Eun-Ah

PA Bentury K. K., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11158126	A2	19990615	JP 1998-162518	19980610
	JP 2949112	B2	19990913		
	KR 235229	B1	19991215	KR 1997-62974	19971126
	US 6096925	A	20000801	US 1998-88784	19980601
	US 6176906	B1	20010123	US 2000-479049	20000107
PRAI	KR 1997-62974	A	19971126		
	US 1998-88784	A3	19980601		

OS MARPAT 131:46119

AB Quaternary ammonium salts  $\text{R1OCH}_2\text{CH}(\text{OH})\text{CH}_2\text{N}+\text{R}_4(\text{CH}_2\text{CH}_2\text{OR}_2)\text{CH}_2\text{CH}_2\text{OR}_3$  X- [I;  $\text{R}_1 = \text{Me}(\text{CH}_2)_n\text{CH}_2$ ,  $\text{Me}(\text{CH}_2)_n\text{C}_6\text{H}_4$ ;  $\text{R}_2, \text{R}_3 = \text{CH}_2:\text{CMeCO}_2\text{CH}_2\text{CH}(\text{OH})\text{CH}_2$ ,  $\text{CH}_2:\text{CHCO}_2\text{CH}_2\text{CH}(\text{OH})\text{CH}_2$ , H;  $\text{R}_2 = \text{R}_3 \neq \text{H}$ ;  $\text{R}_4 = \text{H, Me, Et, Pr}$ ; X =  $\text{MeOSO}_3$ ,  $\text{EtOSO}_3$ ,  $\text{AcO}$ ,  $\text{CF}_3\text{CO}_2$ ,  $\text{Me}(\text{CH}_2)_n\text{CO}_2$ ,  $\text{Me}(\text{CH}_2)_7\text{CH}:\text{CH}(\text{CH}_2)_7\text{CO}_2$ ,  $\text{PhCO}_2$ ,  $\text{PhCH}(\text{OH})\text{CO}_2$ ,  $\text{HO}_2\text{CCH}_2\text{CH}(\text{OH})\text{CO}_2$ , Cl, Br;  $n = 1-16$ ] are prepared by reaction of alkyl glycidyl ethers or alkylphenyl glycidyl ethers with protected di(2-hydroxyethyl)amine, deprotection of the resulting  $\text{R1OCH}_2\text{CH}(\text{OH})\text{CH}_2\text{N}(\text{CH}_2\text{CH}_2\text{OP1})\text{CH}_2\text{CH}_2\text{OP1}$  ( $\text{R}_1 = \text{same as above}$ ; P1 = alc.-protecting group), reaction of the deprotection products with glycidyl (meth)acrylate, and reaction of the resulting tertiary amines with  $\text{R}_4\text{X}$  ( $\text{R}_4, \text{X} = \text{same as above}$ ). Antifogging comps. contain I 3-40, oligomers having  $\geq 2$  acrylic groups 18-90, monomers having  $\geq 1$  acrylic group 5-40, and radical photopolymer. initiators 2-8%. Hybrid antifogging comps. contain I 3-40, oligomers having  $\geq 2$  acrylic groups 4-81, monomers having  $\geq 1$  acrylic group 6-26, monomers having  $\geq 1$  vinyl ether group 8-26, cationic photopolymer. initiators 1-5, and radical photopolymer. initiators 1-5%. Thus, reaction of dodecyl glycidyl ether with di(tert-butyldimethylsilyloxyethyl)amine, deprotection of the product, and reaction of the product with glycidyl methacrylate and  $\text{Me}_2\text{SO}_4$  gave [N-[2-(2-hydroxy-3-methacryloyloxy)propoxy]ethyl,N-(2-hydroxy-3-dodecyloxy)propyl,N-(2-hydroxy)ethyl,N-methyl]ammonium Me sulfate (II). A glass plate was coated with an antifogging composition containing II 30, a polyurethane acrylate (CN 985B88) 40, tripropylene glycol diacrylate (SR 306) 4, trimethylolpropane triacrylate (SR 351) 5, 1-hydroxycyclohexyl Ph ketone (Irgacure 184) 3, bis(4-diphenylsulfoniophenyl)sulfide bis(hexafluorophosphate) (CD 1011) 3, and triethylene glycol divinyl ether (DVE 3) 15% and UV-irradiated to form a cured film showing good hardness and antifogging properties.

IT 227621-22-9P, CN 985B88-DVE 3-[N-[2-(2-hydroxy-3-methacryloyloxy)propoxy]ethyl,N-(2-hydroxy-3-dodecyloxy)propyl,N-(2-hydroxy)ethyl,N-methyl]ammonium methyl sulfate-SR 306-SR 351 copolymer  
227621-23-0P 227621-24-1P 227621-25-2P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

RN 227621-22-9 CAPLUS

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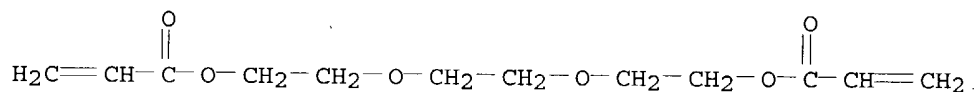
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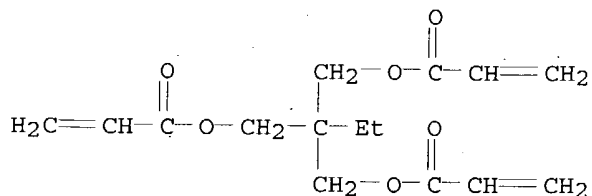
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3 ( D1—Me )

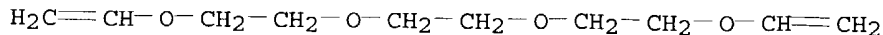
CM 3

CMF C15 H20 O6



CM 4

CMF C10 H18 O4



CM 5

CRN 227596-14-7

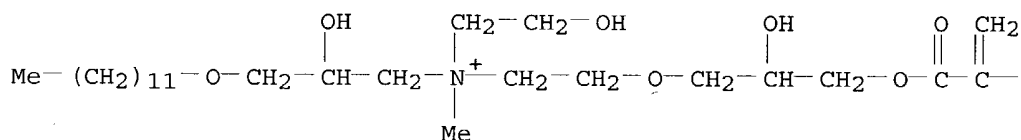
CMF C27 H54 N O7 . C H3 O4 S

CM 6

CRN 227596-13-6

CMF C27 H54 N O7

PAGE 1-A



PAGE 1-B

— Me

CM 7

CRN 21228-90-0

CMF C H3 O4 S

Me-O-SO<sub>3</sub><sup>-</sup>

RN 227621-23-0 CAPLUS

CN 1-Propanaminium, 3-(dodecyloxy)-2-hydroxy-N,N-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-, methyl sulfate (salt), polymer with CN 985B88, 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate and 3,6,9,12-tetraoxatetradeca-1,13-diene (9CI) (CA INDEX NAME)

CM 1

CRN 227620-10-2

CMF Unspecified

CCI PMS, MAN

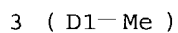
\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

CM 2

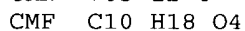
CRN 42978-66-5

CMF C15 H24 O6

CCI IDS



CMF C15 H20 O6



CMF C34 H64 N O10

PAGE 1-B

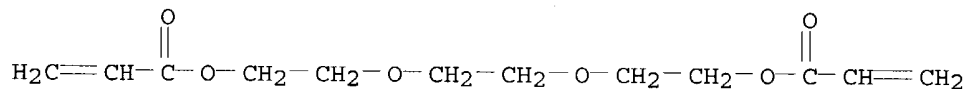
 $\text{--- Me}$

CMF C H3 O4 S

CN Octadecanoic acid, compd. with 3-[2-[[3-(dodecyloxy)-2-hydroxypropyl](2-hydroxyethyl)amino]ethoxy]-2-hydroxypropyl 2-methyl-2-propenoate (1:1), polymer with CN 985B88, 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl] di-2-propenoate, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate and 3,6,9,12-tetraoxatetradeca-1,13-diene (9CI) (CA INDEX NAME)

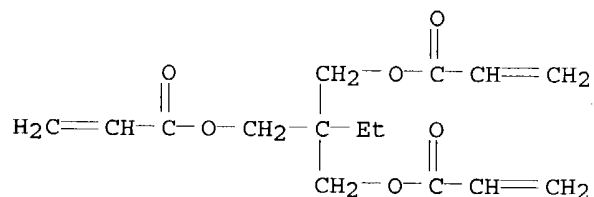
CCI PMS, MAN

CCI    IDS



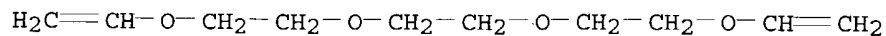
3 ( D1—Me )

CMF C15 H20 O6



CMF C10 H18 O4





CM 5

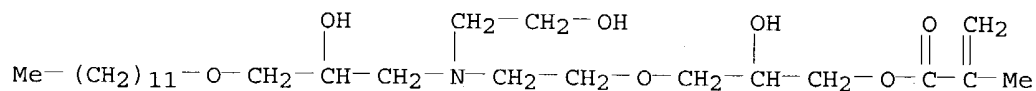
CRN 227596-19-2

CMF C26 H51 N O7 . C18 H36 O2

CM 6

CRN 227596-18-1

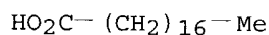
CMF C26 H51 N O7



CM 7

CRN 57-11-4

CMF C18 H36 O2



RN 227621-25-2 CAPLUS

CN Octadecanoic acid, compd. with [[3-(dodecyloxy)-2-hydroxypropyl]imino]bis[2,1-ethanediylxy(2-hydroxy-3,1-propanediyl)] bis(2-methyl-2-propenoate) (1:1), polymer with CN 985B88, 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate, (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate and 3,6,9,12-tetraoxatetradeca-1,13-diene (9CI) (CA INDEX NAME)

CM 1

CRN 227620-10-2

CMF Unspecified

CCI PMS, MAN

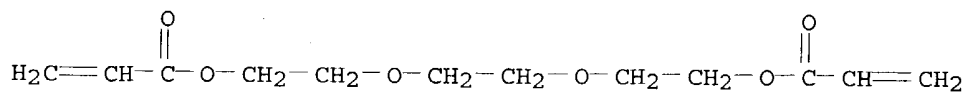
\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

CM 2

CRN 42978-66-5

CMF C15 H24 O6

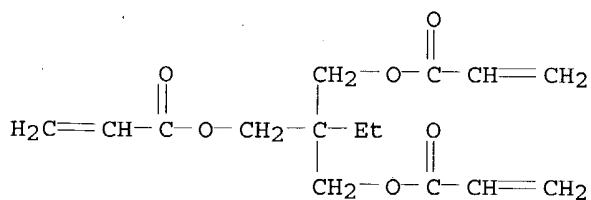
CCI IDS



CM 3

CRN 15625-89-5

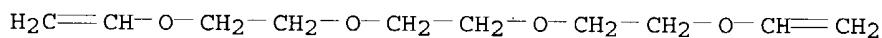
CMF C15 H20 O6



CM 4

CRN 765-12-8

CMF C10 H18 O4



CM 5

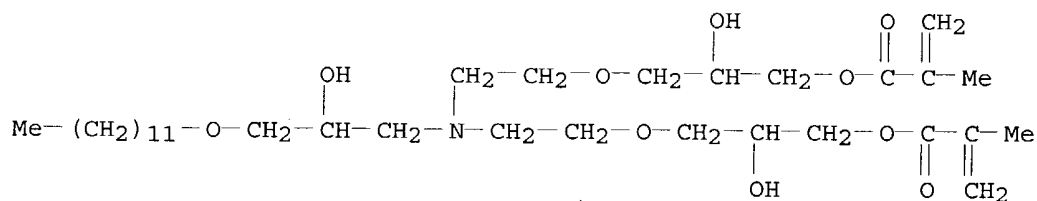
CRN 227596-21-6

CMF C33 H61 N O10 . C18 H36 O2

CM 6

CRN 227596-20-5

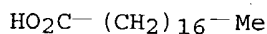
CMF C33 H61 N O10



CM 7

CRN 57-11-4

CMF C18 H36 O2



RN 227621-26-3 CAPLUS

CN 1-Propanaminium, 3-(dodecyloxy)-2-hydroxy-N-(2-hydroxyethyl)-N-[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-, methyl sulfate (salt), polymer with CN 985B88, 3-(dodecyloxy)-2-hydroxy-N,N-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-1-propanaminium methyl sulfate (salt), 3-[2-[[3-(dodecyloxy)-2-hydroxypropyl](2-hydroxyethyl)amino]ethoxy]-2-hydroxypropyl 2-methyl-2-propenoate octadecanoate (salt), [[3-(dodecyloxy)-2-

CM 1

CMF Unspecified

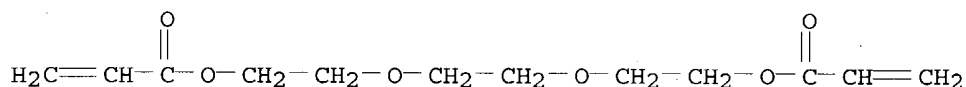
CCI PMS, MAN

\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

CM 2

CMF C15 H24 O6

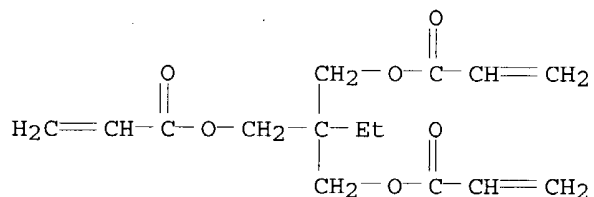
CCI    IDS



3 ( D1-Me )

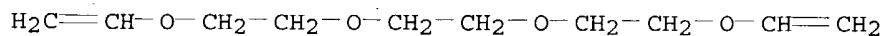
CM 3

CMF C15 H20 O6



CM 4

CMF C10 H18 O4

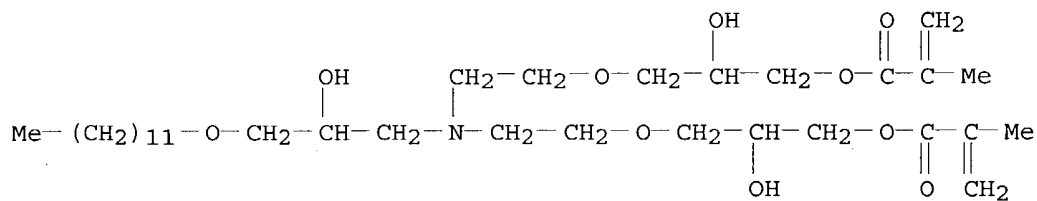


CM 5

CMF C33 H61 N O10 . C18 H36 O2

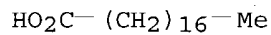
CM 6

CMF C33 H61 N O10



CM 7

CMF C18 H36 O2

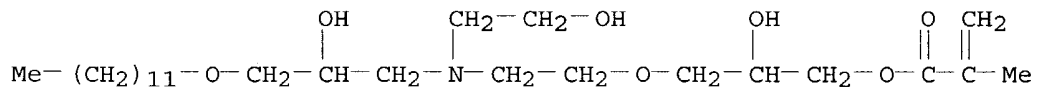


CM 8

CMF C26 H51 N O7 . C18 H36 O2

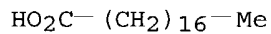
CM 9

CMF C26 H51 N 07



CM 10

CMF C18 H36 O2



CM 11

CMF C34 H64 N O10 . C H3 O4 S

CM 12

CMF C34 H64 N O10

$$\text{Me}-(\text{CH}_2)_{11}-\text{O}-\text{CH}_2-\overset{\text{OH}}{\underset{|}{\text{CH}}}-\text{CH}_2-\overset{\text{Me}}{\underset{\text{CH}_2-\text{CH}_2-\text{O}-\text{CH}_2-\overset{\text{OH}}{\underset{|}{\text{CH}}}-\text{CH}_2-\text{O}-\overset{\text{O}}{\parallel}\text{C}-\overset{\text{CH}_2}{\parallel}\text{C}-}{\text{N}^+}}-\text{CH}_2-\text{CH}_2-\text{O}-\text{CH}_2-\overset{\text{OH}}{\underset{|}{\text{CH}}}-\text{CH}_2-\text{O}-\overset{\text{O}}{\parallel}\text{C}-\overset{\text{CH}_2}{\parallel}\text{C}-\text{Me}$$

— Me

CRN 21228-90-0  
CMF C H3 O4 S

$$\text{Me}-\text{O}-\text{SO}_3^-$$

CRN 227596-14-7  
CMF C27 H54 N 07 . C H3 O4 S

CRN 227596-13-6  
CMF C27 H54 N O7

$$\text{Me}-(\text{CH}_2)_{11}-\text{O}-\text{CH}_2-\overset{\text{OH}}{\underset{|}{\text{CH}}}-\text{CH}_2-\overset{\text{CH}_2-\text{CH}_2-\text{OH}}{\underset{\text{Me}}{\text{N}^+}}-\text{CH}_2-\text{CH}_2-\text{O}-\text{CH}_2-\overset{\text{OH}}{\underset{|}{\text{CH}}}-\text{CH}_2-\text{O}-\overset{\text{O}}{\underset{||}{\text{C}}}-\overset{\text{CH}_2}{\underset{||}{\text{C}}}-$$
 $\text{---Me}$ 

CRN 21228-90-0  
CMF C H3 O4 S

$$\text{Me}-\text{O}-\text{SO}_3^-$$

RN 227621-27-4 CAPLUS

CN 1-Propanaminium, 3-(dodecyloxy)-2-hydroxy-N,N-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-, methyl sulfate (salt), polymer with CN 985B88, 3-(dodecyloxy)-2-hydroxy-N-(2-hydroxyethyl)-N-[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-1-propanaminium methyl sulfate (salt), 3-[2-[3-(dodecyloxy)-2-hydroxypropyl]-2-hydroxyethyl]amino]ethoxy]-2-hydroxypropyl 2-methyl-2-propenoate octadecanoate (salt), [[3-(dodecyloxy)-2-hydroxypropyl]imino]bis[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] bis(2-methyl-2-propenoate) octadecanoate (salt), 2-ethyl-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate and (1-methyl-1,2-ethanediyl)bis[oxy(methyl-2,1-ethanediyl)] di-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 227620-10-2

CMF Unspecified

CCI PMS, MAN

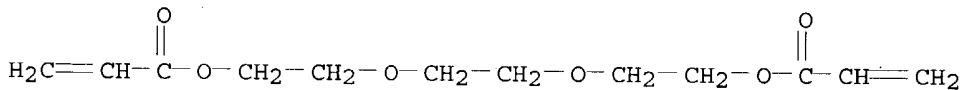
\*\*\* STRUCTURE DIAGRAM IS NOT AVAILABLE \*\*\*

CM 2

CRN 42978-66-5

CMF C15 H24 O6

CCI    IDS

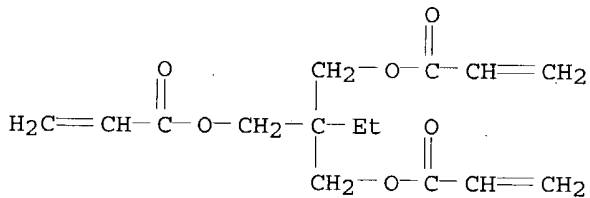


3 ( D1—Me )

CM 3

CRN 15625-89-5

CMF C15 H20 O6



CM 4

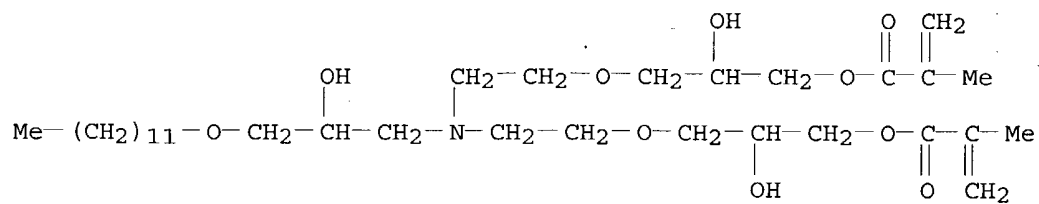
CRN 227596-21-6

CMF C33 H61 N O10 . C18 H36 O2

CM 5

CRN 227596-20-5

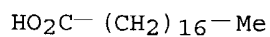
CMF C33 H61 N O10



CM 6

CRN 57-11-4

CMF C18 H36 O2



CM 7

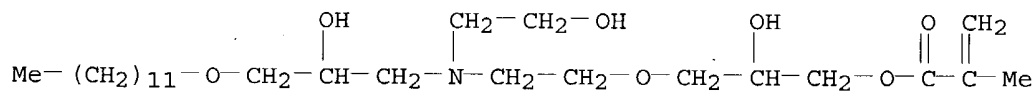
CRN 227596-19-2

CMF C26 H51 N O7 . C18 H36 O2

CM 8

CRN 227596-18-1

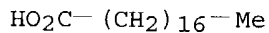
CMF C26 H51 N O7



CM 9

CRN 57-11-4

CMF C18 H36 O2



CM 10

CRN 227596-17-0

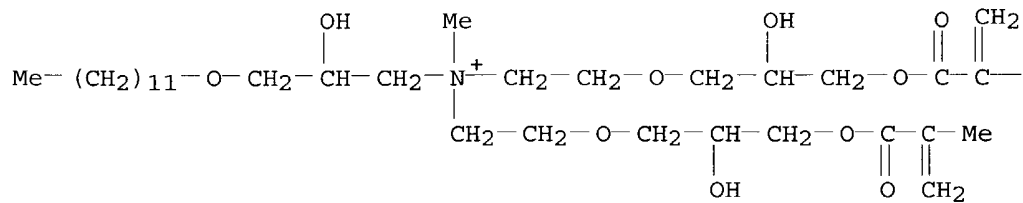
CMF C34 H64 N O10 . C H3 O4 S

CM 11

CRN 227596-16-9

CMF C34 H64 N O10

PAGE 1-A



PAGE 1-B

— Me

CM 12

CRN 21228-90-0  
CMF C H3 O4 S

Me—O—SO<sub>3</sub><sup>−</sup>

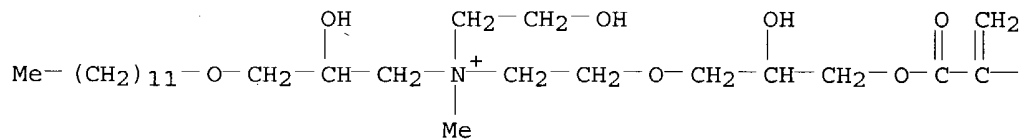
CM 13

CRN 227596-14-7  
CMF C27 H54 N O7 . C H3 O4 S

CM 14

CRN 227596-13-6  
CMF C27 H54 N O7

PAGE 1-A



PAGE 1-B

— Me

CM 15

CRN 21228-90-0  
CMF C H3 O4 S

Me—O—SO<sub>3</sub><sup>−</sup>



IT 227596-14-7P 227596-17-0P 227596-19-2P

227596-21-6P

RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)

(preparation of (meth)acryloyl-containing quaternary ammonium salts for photocurable antifogging coatings)

RN 227596-14-7 CAPLUS

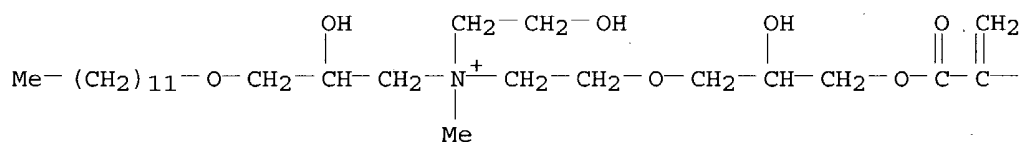
CN 1-Propanaminium, 3-(dodecyloxy)-2-hydroxy-N-(2-hydroxyethyl)-N-[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-, methyl sulfate (salt) (9CI) (CA INDEX NAME)

CM 1

CRN 227596-13-6

CMF C27 H54 N O7

PAGE 1-A



PAGE 1-B

— Me

CM 2

CRN 21228-90-0

CMF C H3 O4 S

Me-O-SO<sub>3</sub><sup>-</sup>

RN 227596-17-0 CAPLUS

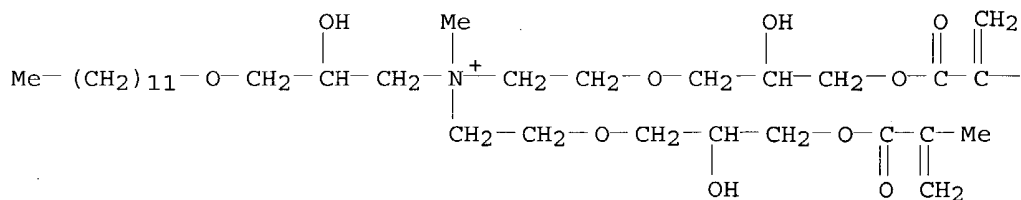
CN 1-Propanaminium, 3-(dodecyloxy)-2-hydroxy-N,N-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-N-methyl-, methyl sulfate (salt) (9CI) (CA INDEX NAME)

CM 1

CRN 227596-16-9

CMF C34 H64 N O10

PAGE 1-A



— Me

CM 2

CRN 21228-90-0

CMF C H3 O4 S

Me—O—SO<sub>3</sub><sup>-</sup>

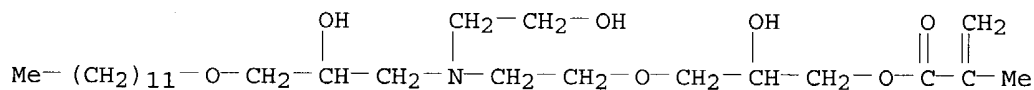
RN 227596-19-2 CAPLUS

CN Octadecanoic acid, compd. with 3-[2-[[3-(dodecyloxy)-2-hydroxypropyl] (2-hydroxyethyl)amino]ethoxy]-2-hydroxypropyl 2-methyl-2-propenoate (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 227596-18-1

CMF C26 H51 N O7



CM 2

CRN 57-11-4

CMF C18 H36 O2

HO<sub>2</sub>C—(CH<sub>2</sub>)<sub>16</sub>—Me

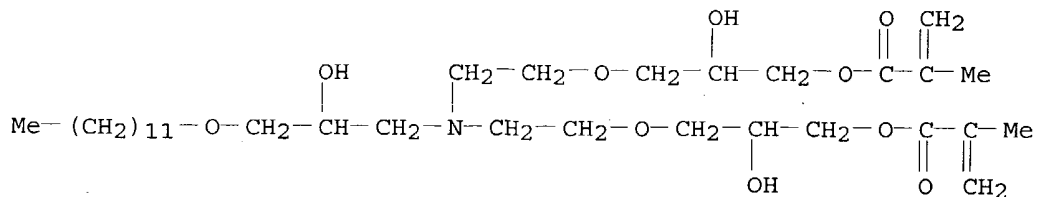
RN 227596-21-6 CAPLUS

CN Octadecanoic acid, compd. with [[3-(dodecyloxy)-2-hydroxypropyl]imino]bis[2,1-ethanedioxy(2-hydroxy-3,1-propanediyl)] bis(2-methyl-2-propenoate) (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 227596-20-5

CMF C33 H61 N O10



CM 2

CRN 57-11-4

CMF C18 H36 O2

HO<sub>2</sub>C-(CH<sub>2</sub>)<sub>16</sub>-Me

L8 ANSWER 8 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1997:490719 CAPLUS

DN 127:197824

TI Photopolymerizable compositions for color filters with high sensitivity at exposure and developability

IN Urano, Toshiyoshi; Ikeda, Shingo; Hino, Etsuko

PA Mitsubishi Chemical Industries Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 14 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09179297	A2	19970711	JP 1995-334825	19951222
PRAI	JP 1995-334825		19951222		

AB The composition, useful for manufacture of color filters, contains an ethylenically-unsatd. compound having aminophenyl or aminocyclohexyl skeleton. The ethylenically-unsatd. compound may have ≥1 structure of I-IV [R1, R2 = H, halo; R3 = (un)substituted C1-20 alkylene; R4 = H, C1-10 alkyl; R5 = H, Me; Z = H, (OH-containing) substituent; m = 0-6; n = 1, 2].

IT 194164-88-0P 194164-90-4P 194164-91-5P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photopolymerizable composition for color filters with high exposure sensitivity and developability)

RN 194164-88-0 CAPLUS

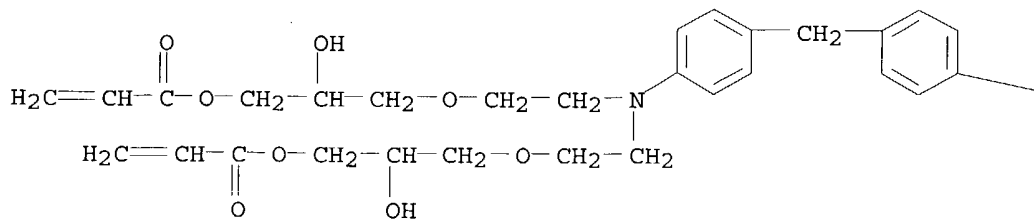
CN 2-Propenoic acid, polymer with ethenylbenzene, [3-hydroxy-4-[(1-oxo-2-propenyl)oxycyclohexyl]methyl 2-propenoate, methylenebis[4,1-phenyleneiminobis[2,1-ethanedioxy(2-hydroxy-3,1-propanediyl)]] tetra-2-propenoate and (1-methylethenyl)benzene (9CI) (CA INDEX NAME)

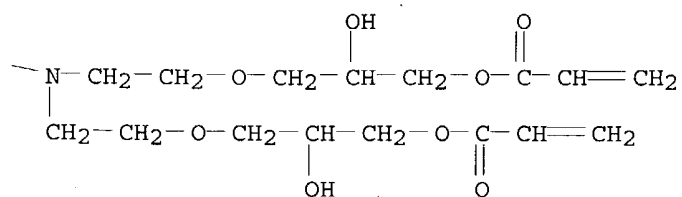
CM 1

CRN 194164-83-5

CMF C45 H62 N2 O16

PAGE 1-A

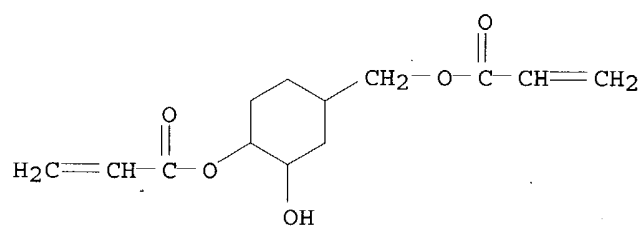




CM 2

CRN 181224-38-4

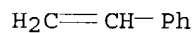
CMF C13 H18 O5



CM 3

CRN 100-42-5

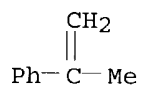
CMF C8 H8



CM 4

CRN 98-83-9

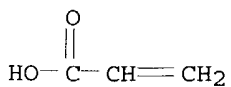
CMF C9 H10



CM 5

CRN 79-10-7

CMF C3 H4 O2



RN 194164-90-4 CAPLUS

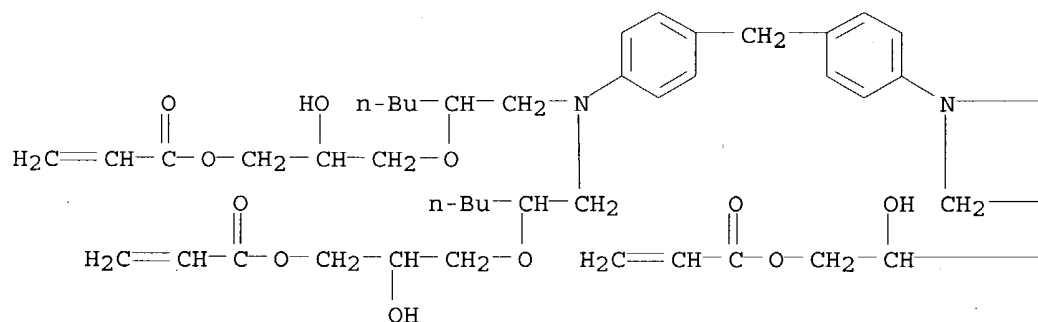
CN 2-Propenoic acid, polymer with ethenylbenzene, [3-hydroxy-4-[(1-oxo-2-propenyl)oxy]cyclohexyl)methyl 2-propenoate, methylenebis[4,1-phenyleneiminobis[(1-butyl-2,1-ethanediyl)oxy(2-hydroxy-3,1-propanediyl)]] tetra-2-propenoate and (1-methylethenyl)benzene (9CI) (CA INDEX NAME)

CM 1

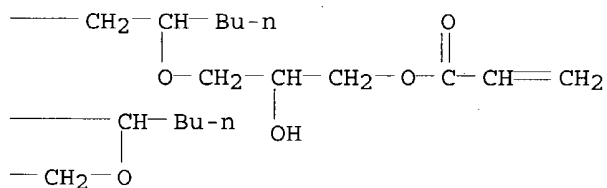
CRN 194164-85-7

CMF C61 H94 N2 O16

PAGE 1-A



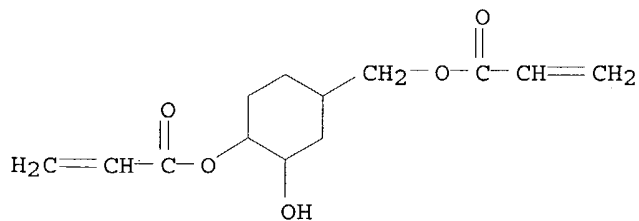
PAGE 1-B



CM 2

CRN 181224-38-4

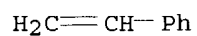
CMF C13 H18 O5



CM 3

CRN 100-42-5

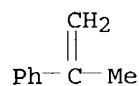
CMF C8 H8



CM 4

CRN 98-83-9

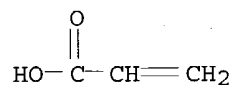
CMF C9 H10



CM 5

CRN 79-10-7

CMF C3 H4 O2



RN 194164-91-5 CAPLUS

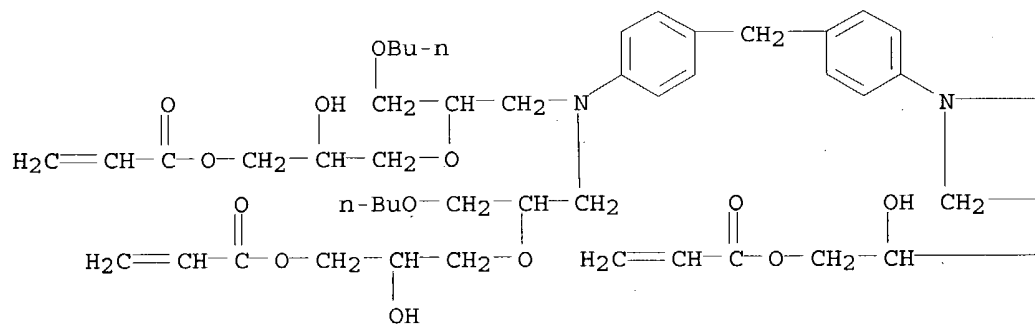
CN 2-Propenoic acid, polymer with ethenylbenzene, [3-hydroxy-4-[(1-oxo-2-propenyl)oxy]cyclohexyl)methyl 2-propenoate, methylenebis[4,1-phenyleneiminobis[[1-(butoxymethyl)-2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)]] tetra-2-propenoate and (1-methylethenyl)benzene (9CI) (CA INDEX NAME)

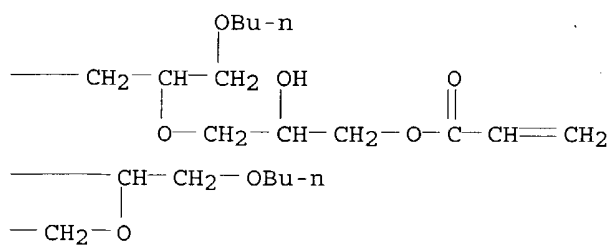
CM 1

CRN 194164-86-8

CMF C65 H102 N2 O20

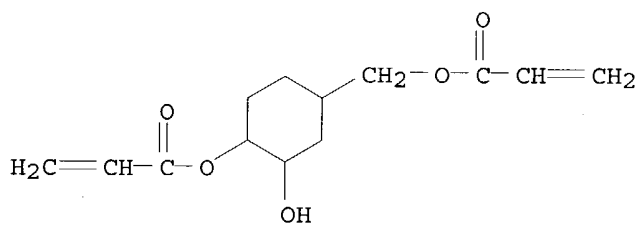
PAGE 1-A





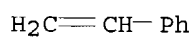
CM 2

CRN 181224-38-4  
CMF C13 H18 O5



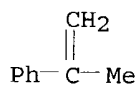
CM 3

CRN 100-42-5  
CMF C8 H8



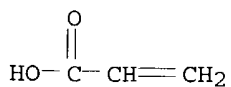
CM 4

CRN 98-83-9  
CMF C9 H10



CM 5

CRN 79-10-7  
CMF C3 H4 O2



IT 194164-83-5 194164-84-6 194164-85-7

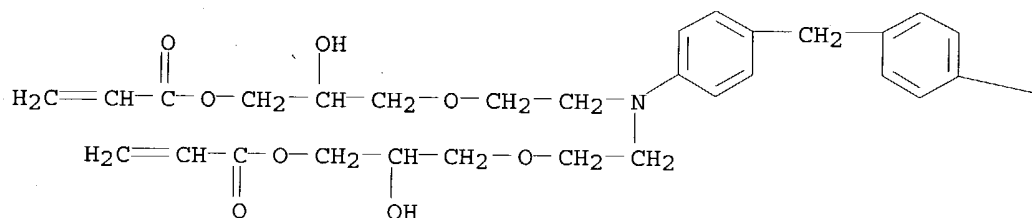
194164-86-8 194164-89-1

RL: TEM (Technical or engineered material use); USES (Uses)  
(photopolymerizable composition for color filters with high exposure sensitivity and developability)

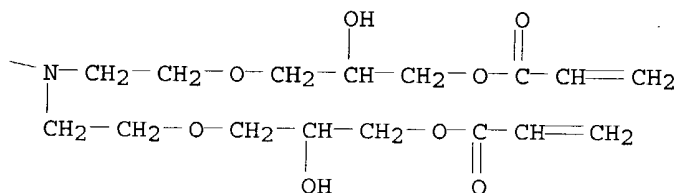
RN 194164-83-5 CAPLUS

CN 2-Propenoic acid, methylenebis[4,1-phenylenenitrilobis[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)]] ester (9CI) (CA INDEX NAME)

PAGE 1-A



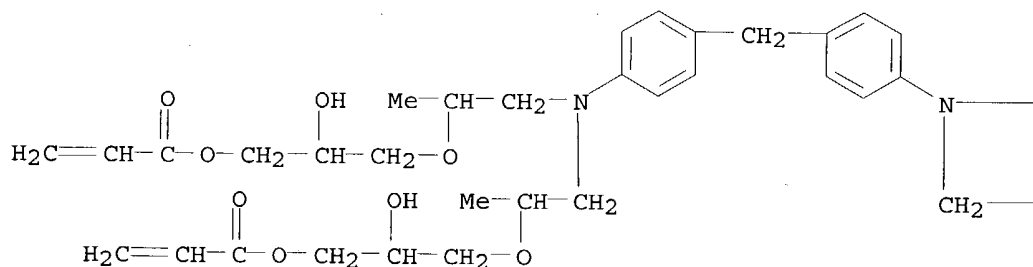
PAGE 1-B



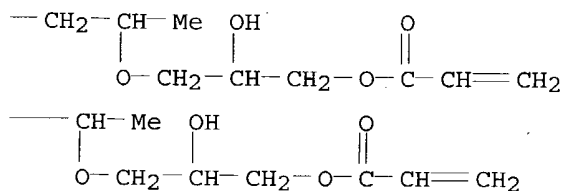
RN 194164-84-6 CAPLUS

CN 2-Propenoic acid, methylenebis[4,1-phenylenenitrilobis[(1-methyl-2,1-ethanediyl)oxy(2-hydroxy-3,1-propanediyl)]] ester (9CI) (CA INDEX NAME)

PAGE 1-A

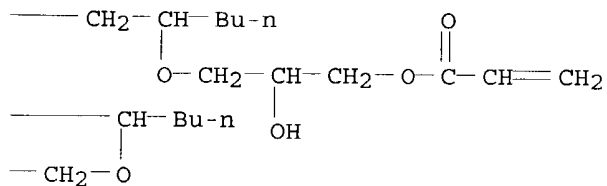
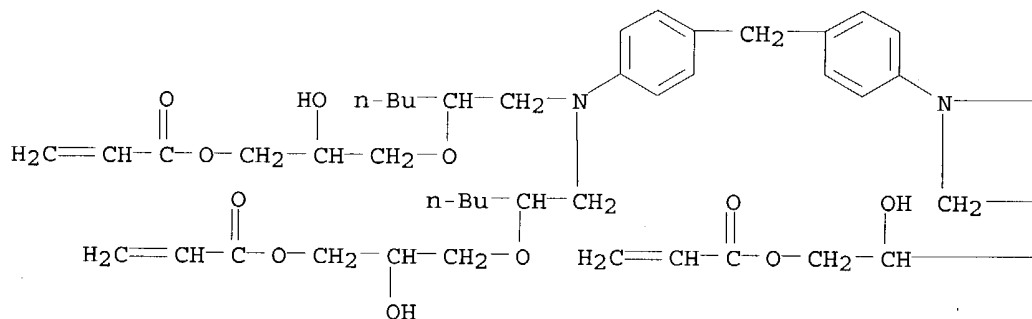






RN 194164-85-7 CAPLUS

CN 2-Propenoic acid, methylenebis[4,1-phenylenenitrilobis[(1-butyl-2,1-ethanediyl)oxy(2-hydroxy-3,1-propanediyl)]] ester (9CI) (CA INDEX NAME)



RN 194164-86-8 CAPLUS

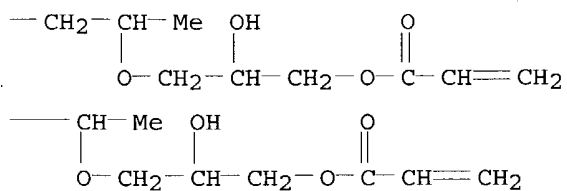
CN 2-Propenoic acid, methylenebis[4,1-phenylenenitrilobis[[1-(butoxymethyl)-  
2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)]] ester (9CI) (CA INDEX  
NAME)

[illegible]
$$\begin{array}{c}
 \text{---CH}_2\text{---CH---CH}_2\text{---OH} \\
 | \qquad \qquad | \\
 \text{O---CH}_2\text{---CH---CH}_2\text{---O---C(=O)---CH=CH}_2 \\
 | \\
 \text{---CH---CH}_2\text{---OBu-n} \\
 | \\
 \text{---CH}_2\text{---O}
 \end{array}$$

CN 2-Propenoic acid, polymer with ethenylbenzene, [3-hydroxy-4-[(1-oxo-2-propenyl)oxy]cyclohexyl)methyl 2-propenoate, methylenebis[4,1-phenyleneiminobis[(1-methyl-2,1-ethanediyl)oxy(2-hydroxy-3,1-propanediyl)]] tetra-2-propenoate and (1-methylethenyl)benzene (9CI) (CA INDEX NAME)

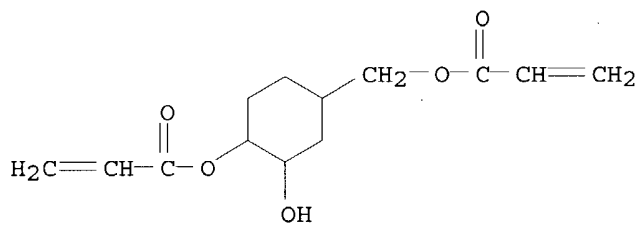
CRN 194164-84-6  
CMF C49 H70 N2 O16

$$\begin{array}{c}
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 \text{H}_2\text{C}=\text{CH}-\overset{\text{O}}{\parallel}\text{C}-\text{O}-\text{CH}_2-\underset{\text{OH}}{\text{CH}}-\text{CH}_2-\text{O}-\underset{\text{Me}-\text{CH}-\text{CH}_2}{\text{N}}
 \end{array}$$



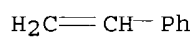
CM 2

CRN 181224-38-4  
CMF C13 H18 O5



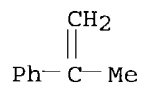
CM 3

CRN 100-42-5  
CMF C8 H8



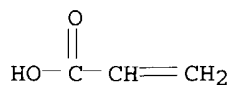
CM 4

CRN 98-83-9  
CMF C9 H10



CM 5

CRN 79-10-7  
CMF C3 H4 O2



L8 ANSWER 9 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1992:140152 CAPLUS  
 DN 116:140152  
 TI Photopolymerization process for preparing printing plates and photoresists  
 IN Zertani, Rudolf; Mohr, Dieter; Matthiessen, Peter  
 PA Hoechst A.-G., Germany  
 SO Ger. Offen., 10 pp.  
 CODEN: GWXXBX

DT Patent  
 LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4013358	A1	19911031	DE 1990-4013358	19900426
	EP 453953	A2	19911030	EP 1991-106188	19910418
	EP 453953	A3	19921202		
	EP 453953	B1	19970924		
	R: BE, DE, ES, FR, GB, IT, NL, SE				
	ES 2106039	T3	19971101	ES 1991-106188	19910418
	FI 9101979	A	19911027	FI 1991-1979	19910424
	CA 2041191	AA	19911027	CA 1991-2041191	19910425
	BR 9101676	A	19911210	BR 1991-1676	19910425
	JP 04261544	A2	19920917	JP 1991-122425	19910425
	JP 3118520	B2	20001218		
PRAI	DE 1990-4013358	A	19900426		

AB Photopolymn. process for preparing printing plates and photoresists. The title photopolymn. process involves irradiating a polymerizable layer containing a polymer binder, a radical polymerizable ethylenically unsatd. compound with  $\geq 1$  ethylenically unsatd. end group(s), and a radical polymerization initiator (e.g. metallocene compound). The imaging material can be irradiated with a visible light ( $>400$  nm) for hardening before, during, or after imagewise-irradiation (heat will release in short time).

IT 123735-16-0

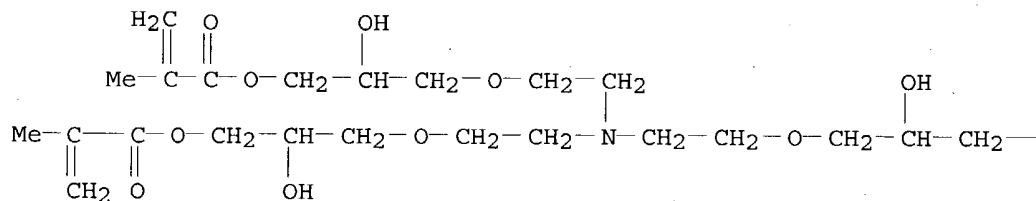
RL: USES (Uses)

(photoresist containing)

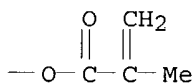
RN 123735-16-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

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L8 ANSWER 10 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1990:488280 CAPLUS  
 DN 113:88280  
 TI Photopolymerizable imaging materials with decreased sensitivity toward oxygen  
 IN Zertani, Rudolf; Mohr, Dieter  
 PA Hoechst A.-G., Germany  
 SO Ger. Offen., 11 pp.  
 CODEN: GWXXBX  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3825836	A1	19900208	DE 1988-3825836	19880729
	EP 352630	A2	19900131	EP 1989-113306	19890720
	EP 352630	A3	19900801		
	EP 352630	B1	19940817		
	R: DE, FR, GB, IT, NL				
	CA 1337677	A1	19951205	CA 1989-606446	19890724
	JP 02103051	A2	19900416	JP 1989-194419	19890728
	JP 2736124	B2	19980402		
	KR 135076	B1	19980418	KR 1989-10797	19890729
	US 5273862	A	19931228	US 1992-913753	19920717
PRAI	DE 1988-3825836	A	19880729		
	US 1989-381832	B1	19890719		

AB Photopolymerizable imaging materials, which are especially useful in preparing lithog. plates, are composed of a support, a photopolymerizable layer, and a top layer that has little permeability to O and contains a polymer that binds O and is completely soluble in water. The top layer may be prepared from poly(vinyl alc.) and a polyalkylenimine. Thus, a lithog. plate prepared from a photopolymerizable imaging material having a top layer prepared from a 7% aqueous poly(vinyl alc.) solution and Polymine P showed excellent storage stability.

IT 123735-16-0

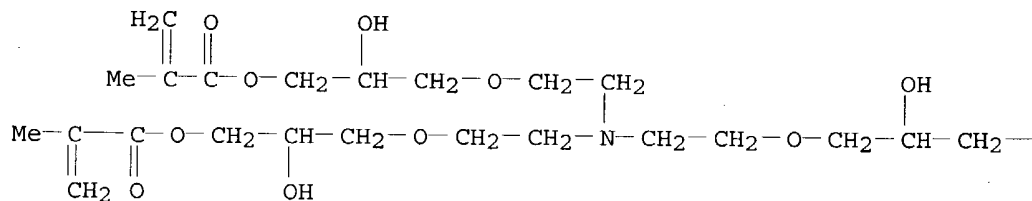
RL: USES (Uses)

(photopolymerizable imaging material containing, with polymer oxygen barrier layer for lithog. plate preparation)

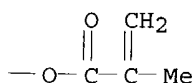
RN 123735-16-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanedioxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



L8 ANSWER 11 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1990:28187 CAPLUS  
 DN 112:28187  
 TI Photopolymerizable mixture and recording material therefrom  
 IN Rode, Klaus; Mohr, Dieter; Frass, Werner; Gersdorf, Joachim  
 PA Hoechst A.-G., Fed. Rep. Ger.  
 SO Eur. Pat. Appl., 18 pp.  
 CODEN: EPXXDW

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 321827	A2	19890628	EP 1988-120774	19881213
	EP 321827	A3	19890906		
	EP 321827	B1	19931110		
	R: DE, FR, GB, NL				
	DE 3743455	A1	19890706	DE 1987-3743455	19871222
	FI 8805876	A	19890623	FI 1988-5876	19881220
	DK 8807117	A	19890623	DK 1988-7117	19881221
	JP 01203414	A2	19890816	JP 1988-320794	19881221
	JP 2736087	B2	19980402		
	BR 8806780	A	19890829	BR 1988-6780	19881221
	US 4985341	A	19910115	US 1988-287279	19881221
	AU 8827393	A1	19890622	AU 1988-27393	19881222
	AU 610961	B2	19910530		
PRAI	DE 1987-3743455	A	19871222		

AB Photopolymerizable mixts. for the preparation of photoresists and printing plates are composed of a polymer binder, an acrylic acid or alkacrylic acid ester of a polyhydric alc. having a group photooxidizable by exposure in the presence of a photoreducible dye (the photooxidizable compound does not contain a urethane group), a photoreducible dye as photoinitiator, and a radiation-cleavable trihalomethyl compound. The mixture has improved sensitivity. Thus, a roughened and hydrophilized Al printing plate was overcoated with a composition containing a Me methacrylate-methacrylic acid copolymer (acid number 110 and average mol. weight 35,000), N[CH<sub>2</sub>CHMeCOCH<sub>2</sub>CH(CH<sub>2</sub>O<sub>2</sub>CCMe:CH<sub>2</sub>)OH]<sub>3</sub>, alc. eosin, and propylene glycol mon-Me ether, dried, imagewise exposed through an edge filter, and developed to give 6 steps.

IT 123735-16-0 124197-91-7 124197-92-8  
 124197-94-0

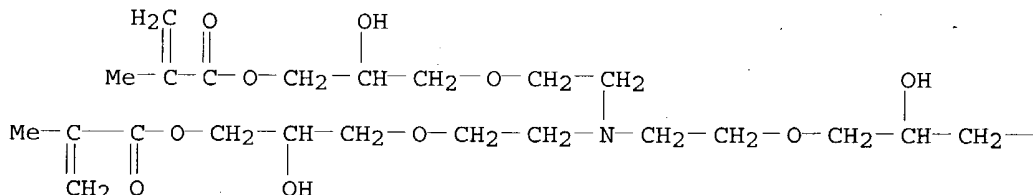
RL: USES (Uses)

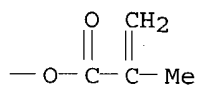
(photopolymerizable compns. containing photoreducible dye photoinitiators and, for photoresists and printing plates)

RN 123735-16-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

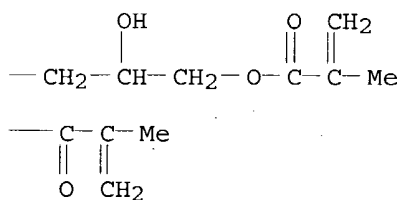
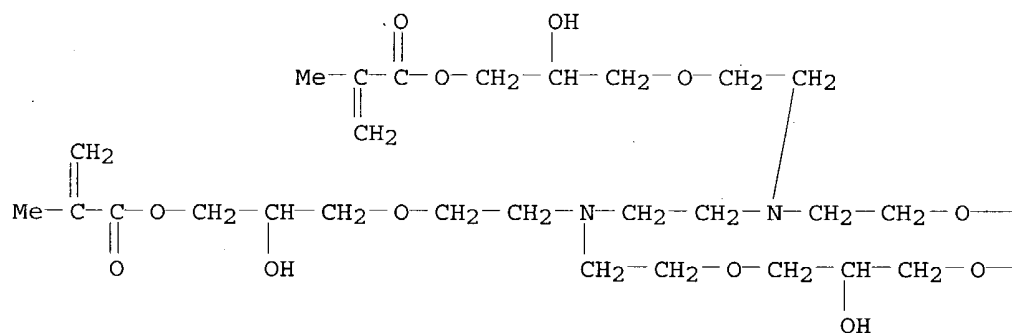
PAGE 1-A





RN 124197-91-7 CAPLUS

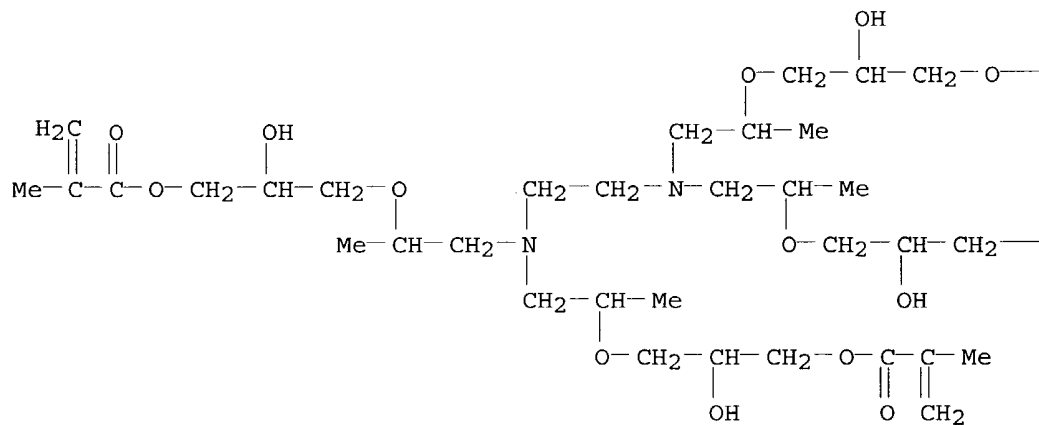
CN 2-Propenoic acid, 2-methyl-, 2,15-dihydroxy-7,10-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]ethyl]-4,13-dioxo-7,10-diaza-hexadecane-1,16-diyl ester (9CI) (CA INDEX NAME)



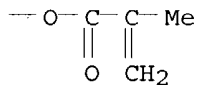
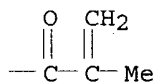
RN 124197-92-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2,15-dihydroxy-7,10-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]propyl]-5,12-dimethyl-4,13-dioxo-7,10-diaza-hexadecane-1,16-diyl ester (9CI) (CA INDEX NAME)

PAGE 1-A



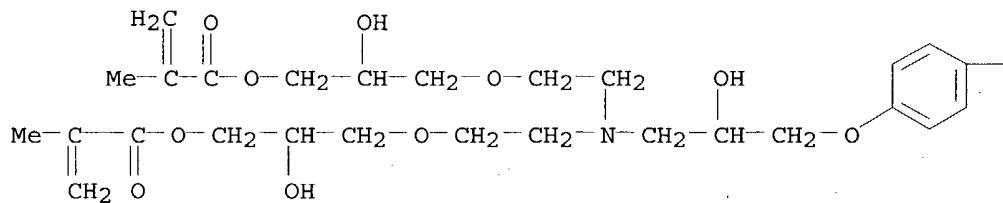
PAGE 1-B



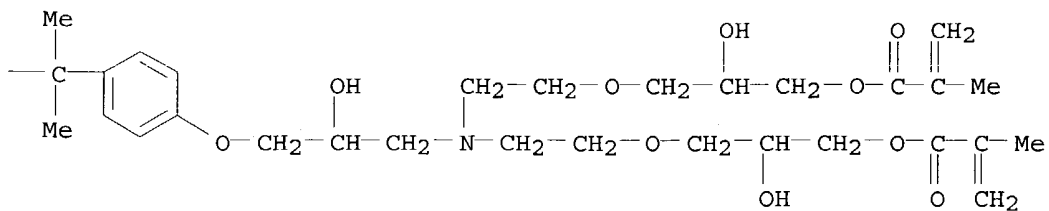
RN 124197-94-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, (1-methylethylidene)bis[4,1-phenyleneoxy(2-hydroxy-3,1-propanediyl)nitrilobis[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

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PAGE 1-B





L8 ANSWER 12 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1990:14306 CAPLUS  
 DN 112:14306  
 TI Photopolymerizable mixture and recording material therefrom  
 IN Rode, Klaus; Mohr, Dieter; Frass, Werner; Gerstorf, Joachim  
 PA Hoechst A.-G., Fed. Rep. Ger.  
 SO Eur. Pat. Appl., 18 pp.  
 CODEN: EPXXDW

DT Patent

LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 321828	A2	19890628	EP 1988-120775	19881213
	EP 321828	A3	19890906		
	EP 321828	B1	19931110		
	R: DE, FR, GB, NL				
	DE 3743457	A1	19890706	DE 1987-3743457	19871222
	FI 8805877	A	19890623	FI 1988-5877	19881220
	DK 8807118	A	19890623	DK 1988-7118	19881221
	BR 8806781	A	19890829	BR 1988-6781	19881221
	JP 02001714	A2	19900108	JP 1988-320795	19881221
	JP 2758179	B2	19980528		
	US 4987055	A	19910122	US 1988-287276	19881221
	AU 8827394	A1	19890622	AU 1988-27394	19881222
	AU 610962	B2	19910530		
	ZA 8809581	A	19890927	ZA 1988-9581	19881222
PRAI	DE 1987-3743457	A	19871222		

AB Photopolymerizable mixts. for the preparation of photoresists and printing plates are composed of a polymer binder, an acrylic acid or alkacrylic acid ester of a polyhydric alc. having a group photooxidizable by a photoreducible dye, a photoreducible benzoxanthene or benzothioxanthene dye as a photoinitiator, a radiation-cleavable trihalomethyl compound, and, optionally, an acridine or phenazine compound as a photoinitiator. The mixts. have increased sensitivity. Thus, a roughened and hydrophilized Al printing plate was overcoated with a composition containing a Me methacrylate-methacrylic acid copolymer (acid number 110 and average mol. wt 35,000), N[CH<sub>2</sub>CHMeCOCH<sub>2</sub>CH(CH<sub>2</sub>O<sub>2</sub>CCMe:CH<sub>2</sub>)OH]<sub>3</sub>, the dye I, 2,4-bis(trichloromethyl)-6-(4-styrylphenyl)-s-triazine, and propylene glycol mono-Me ether, dried, imagewise exposed through an edge filter, and developed to show 4 steps.

IT 123735-16-0 124197-92-8 124197-94-0

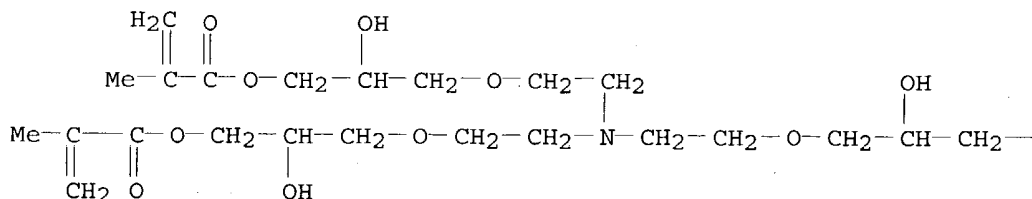
RL: USES (Uses)

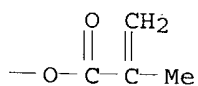
(photopolymerizable compns. containing benzoxanthene or benzothioxanthene derivative photoinitiator and, for photoresists and printing plate fabrication)

RN 123735-16-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanediyl]oxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

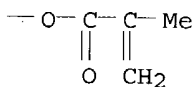
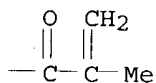
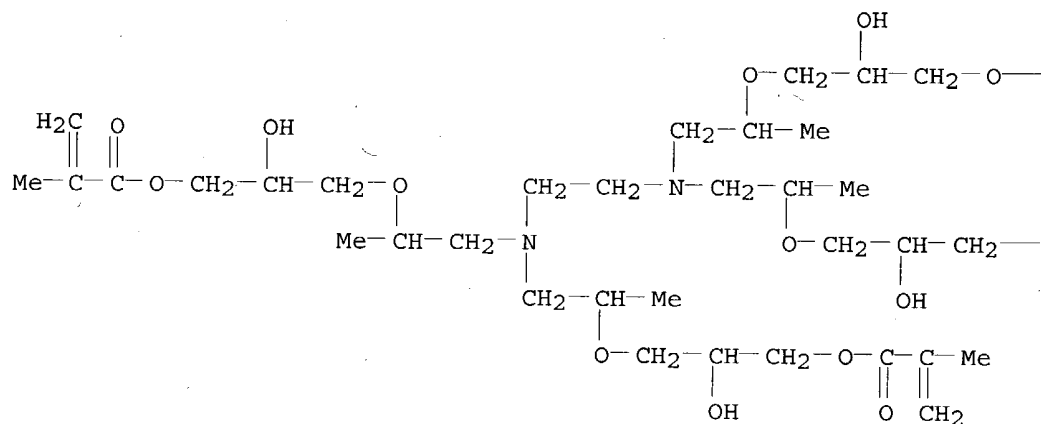
PAGE 1-A





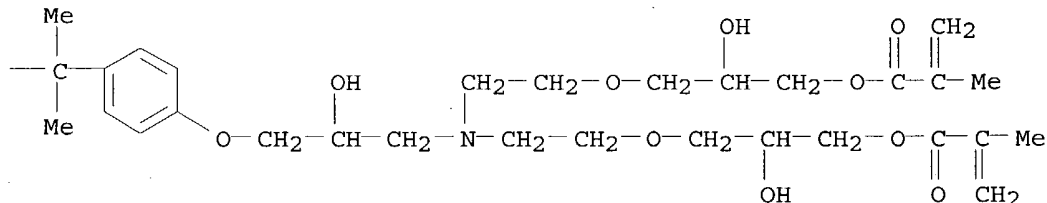
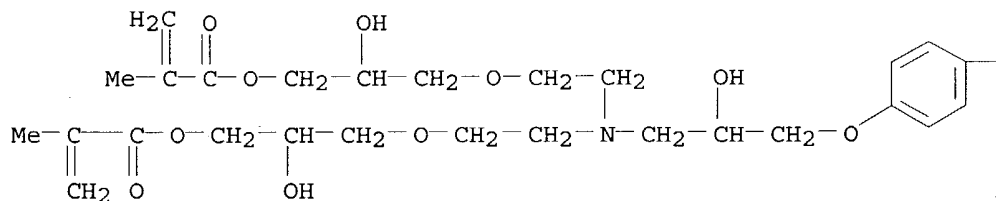
RN 124197-92-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2,15-dihydroxy-7,10-bis[2-[2-hydroxy-3-[(2-methyl-1-oxo-2-propenyl)oxy]propoxy]propyl]-5,12-dimethyl-4,13-dioxo-7,10-diazahexadecane-1,16-diyl ester (9CI) (CA INDEX NAME)



RN 124197-94-0 CAPLUS

CN 2-Propenoic acid, 2-methyl-, (1-methylethylidene)bis[4,1-phenyleneoxy(2-hydroxy-3,1-propanediyl)nitrilobis[2,1-ethanediylloxy(2-hydroxy-3,1-propanediyl)]] ester (9CI) (CA INDEX NAME)



L8 ANSWER 13 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 1989:622175 CAPLUS  
 DN 111:222175  
 TI Photosensitive printing plate for waterless offset printing  
 IN Schlosser, Hans Joachim; Gersdorf, Joachim  
 PA Hoechst A.-G., Fed. Rep. Ger.  
 SO Ger. Offen., 7 pp.  
 CODEN: GWXXBX  
 DT Patent  
 LA German  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 3738863	A1	19890524	DE 1987-3738863	19871116
	EP 316705	A2	19890524	EP 1988-118536	19881108
	EP 316705	A3	19900801		
	EP 316705	B1	19940330		
	R: CH, DE, FR, GB, LI				
	US 4956262	A	19900911	US 1988-270343	19881114
	JP 01155352	A2	19890619	JP 1988-287885	19881116
	JP 2746617	B2	19980506		
PRAI	DE 1987-3738863	A	19871116		

AB Photosensitive printing plates for waterless lithog. are composed of a support, a photosensitive layer containing a diazonium salt polycondensate, a radically polymerizable compound with  $\geq 1$  terminal ethylenically unsatd. group and a b.p.  $\geq 100$  at normal pressure, a photopolymerization initiator, and, optionally, a binder, and an ink-repelling silicone rubber layer. The printing plates have a higher sensitivity than corresponding plates whose photosensitive layer contains only a photopolymerizable mixture or only a diazonium salt polycondensate. Thus, a typical plate consisted of an electrolytically roughened and anodically oxidized Al plate coated with a photosensitive layer from a composition containing a

3-methoxydiphenylamine-

4-diazonium salt-4,4'-bismethoxymethyldiphenyl ether mesitylenesulfonate, poly(vinyl butyral) maleate, N-methyldiethanolamine dimethacrylate (I), H<sub>3</sub>PO<sub>4</sub>, phenylazodiphenylamine, and 2-methoxyethanol, and a silicone rubber layer. The plate showed improved sensitivity over a I-free control.

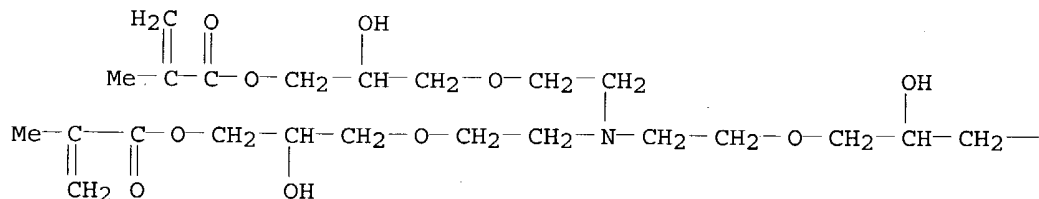
IT 123735-16-0

RL: USES (Uses)

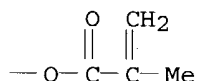
(waterless presensitized lithog. plates with photosensitive layer

containing diazonium salt in)  
 RN 123735-16-0 CAPLUS  
 CN 2-Propenoic acid, 2-methyl-, nitrilotris[2,1-ethanedioxy(2-hydroxy-3,1-propanediyl)] ester (9CI) (CA INDEX NAME)

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PAGE 1-B



L8 ANSWER 14 OF 14 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1969:48346 CAPLUS

DN 70:48346

TI Soil stabilization with crosslinked acrylate polymers

IN Higashimura, Einosuke; Ishii, Masao; Ishikawa, Yoshio

PA Mitsubishi Rayon Co., Ltd.

SO U.S., 5 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3417567	A	19681224	US 1967-623557	19670316
	NL 6704061	A	19670919	NL 1967-4061	19670317
PRAI	JP 1966-16806	A	19660318		
	JP 1966-16807	A	19660318		

AB An aqueous soluble of an acrylate monomer and 1 or more addnl. copolymerizable monomers is mixed with soil in the presence of a redox catalyst and polymerized to provide a water-insol. stable soil aggregate. The process is used to strengthen foundations and to provide grouting in civil engineering applications. Thus, an aqueous solution containing 9 parts Ca acrylate

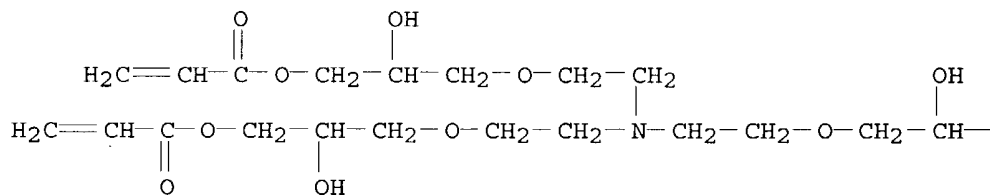
(I) and 0.1 part dimethylaminopropionitrile in 50 parts H<sub>2</sub>O was mixed with a solution of 0.1 part (NH<sub>4</sub>)<sub>2</sub>S<sub>2</sub>O<sub>8</sub> and 20 parts H<sub>2</sub>O at 20°. Polymerization occurred after .apprx.5 min. and a gel formed. I and a catalyst were mixed with sand in a mold and polymerization started after 15 min. A water-insol. product was obtained after 3 hrs. Other monomers used were glycerol diacrylate, the reaction product of glycidyl acrylate with aminoethyl acrylate, ethylenediamine, triethanolamine, and tetraethylene glycol monoacrylate, Mg acrylate, hydroxyethyl methacrylate, dimethylaminoethyl methacrylate, the reaction product of glycerol with methacrylate, and acrylamide. Catalyst systems contained Na<sub>2</sub>S<sub>2</sub>O<sub>3</sub>, NaHSO<sub>3</sub>, and K<sub>2</sub>S<sub>2</sub>O<sub>8</sub>. The compression strength of sand aggregates ranged from 0.3-7.1 kg./cm.<sup>2</sup> with corresponding water permeation coefficient of 4 + 10<sup>-4</sup> - 9.1 + 10<sup>-8</sup> cm./sec.

IT 28390-18-3P  
 RL: SPN (Synthetic preparation); PREP (Preparation)  
 (preparation of)  
 RN 28390-18-3 CAPLUS  
 CN Acrylic acid, 1,1',1''-triester with 3,3',3''-  
 [nitrilotris(ethyleneoxy)]tri-1,2-propanediol, polymer with acrylamide  
 (8CI) (CA INDEX NAME)

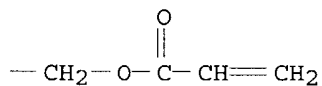
CM 1

CRN 45312-64-9  
 CMF C24 H39 N O12

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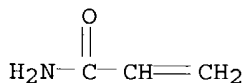


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CM 2

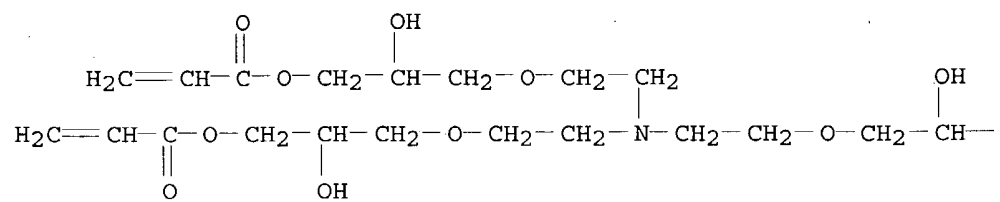
CRN 79-06-1  
 CMF C3 H5 N O



IT 28390-18-3  
 RL: USES (Uses)  
 (soil stabilization with)  
 RN 28390-18-3 CAPLUS  
 CN Acrylic acid, 1,1',1''-triester with 3,3',3''-  
 [nitrilotris(ethyleneoxy)]tri-1,2-propanediol, polymer with acrylamide  
 (8CI) (CA INDEX NAME)

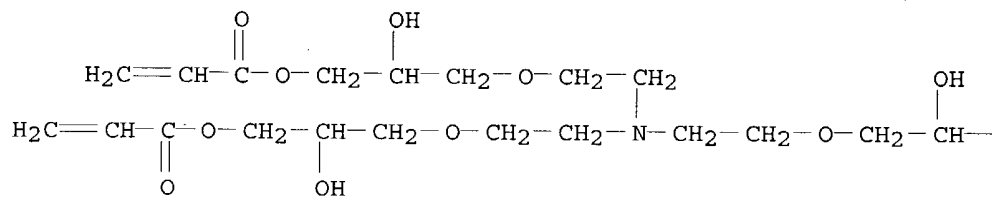
CM 1

CRN 45312-64-9  
 CMF C24 H39 N O12

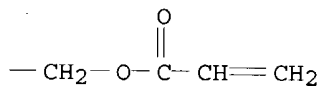


IT 28390-18-3  
 RL: USES (Uses)  
 (soil stabilization with)  
 RN 28390-18-3 CAPLUS  
 CN Acrylic acid, 1,1',1''-triester with 3,3',3''-  
 [nitrilotris(ethyleneoxy)]tri-1,2-propanediol, polymer with acrylamide  
 (8CI) (CA INDEX NAME)  
 CM 1  
 CRN 45312-64-9  
 CMF C24 H39 N O12

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CM 2  
 CRN 79-06-1  
 CMF C3 H5 N O

